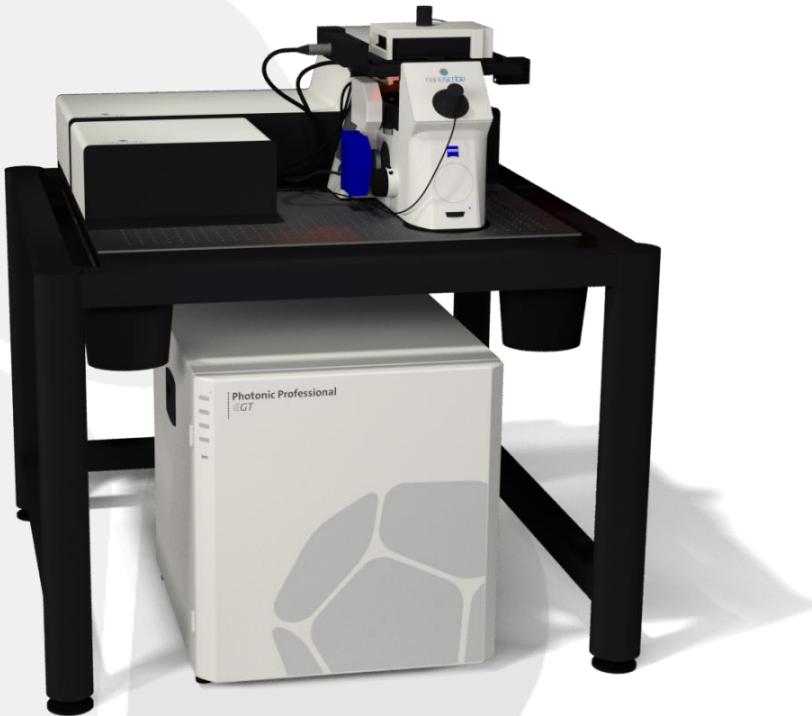


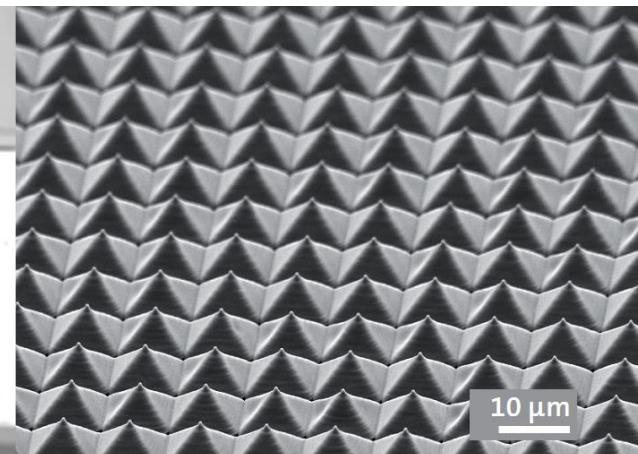
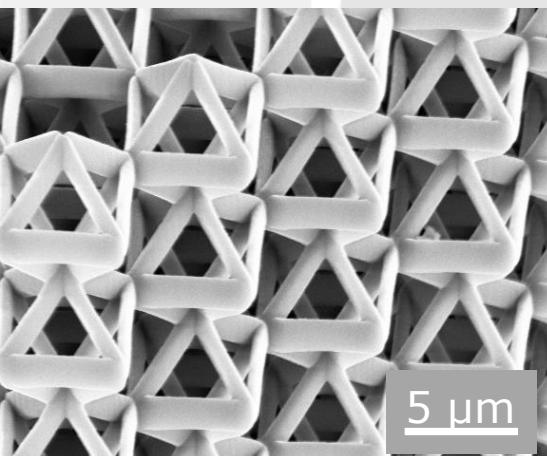


nanoscribe

3D μ -Printing by Direct Laser Writing

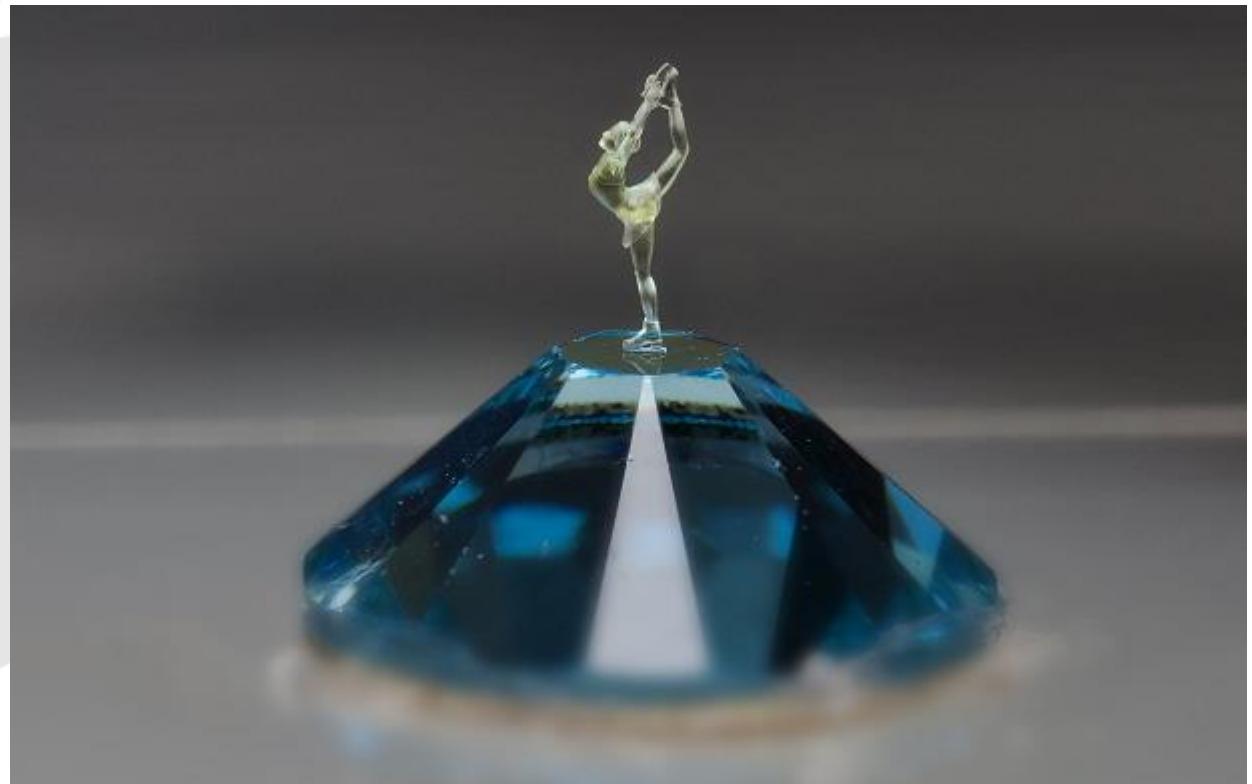


Nanoscribe GmbH
Sofía Rodríguez



Overview

- Introduction: Nanoscribe GmbH
- Technology: Direct Laser Writing
- Materials
- Applications
- Summary



Who We Are ...

Company History:

- Spin-off from the Karlsruhe Institute of Technology (KIT)
group: Prof. Dr. Martin Wegener
- 2007: Foundation
- Market and technology leader
- 40 employees
- >100 systems sold
- Feb. 2014: Prism Award
“Advanced Manufacturing”



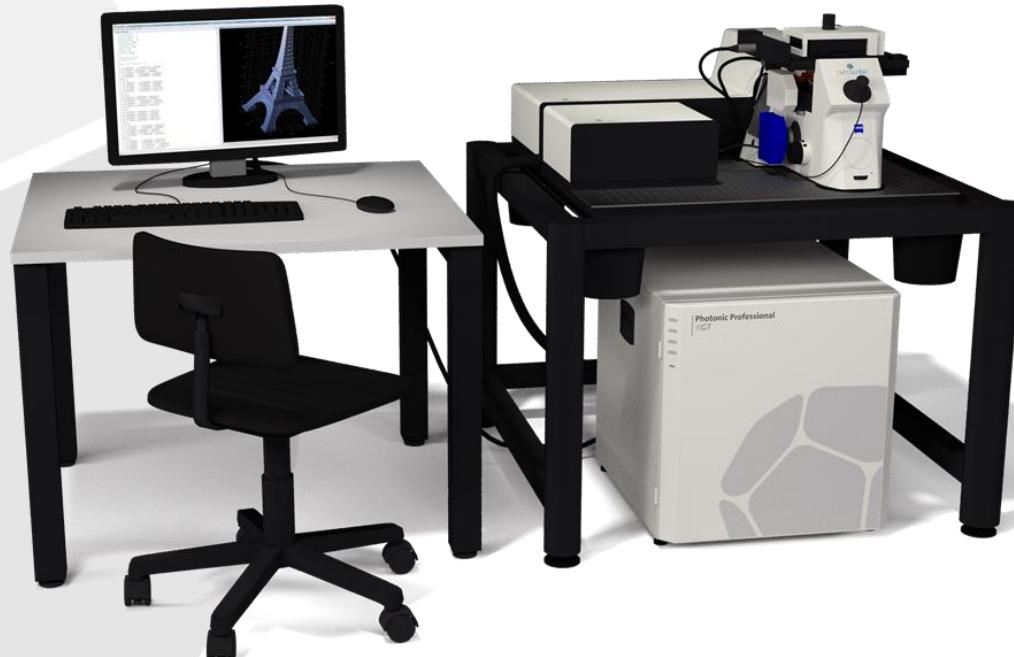
Products:

- 3D laser lithography systems
- Photoresists



nanscribe

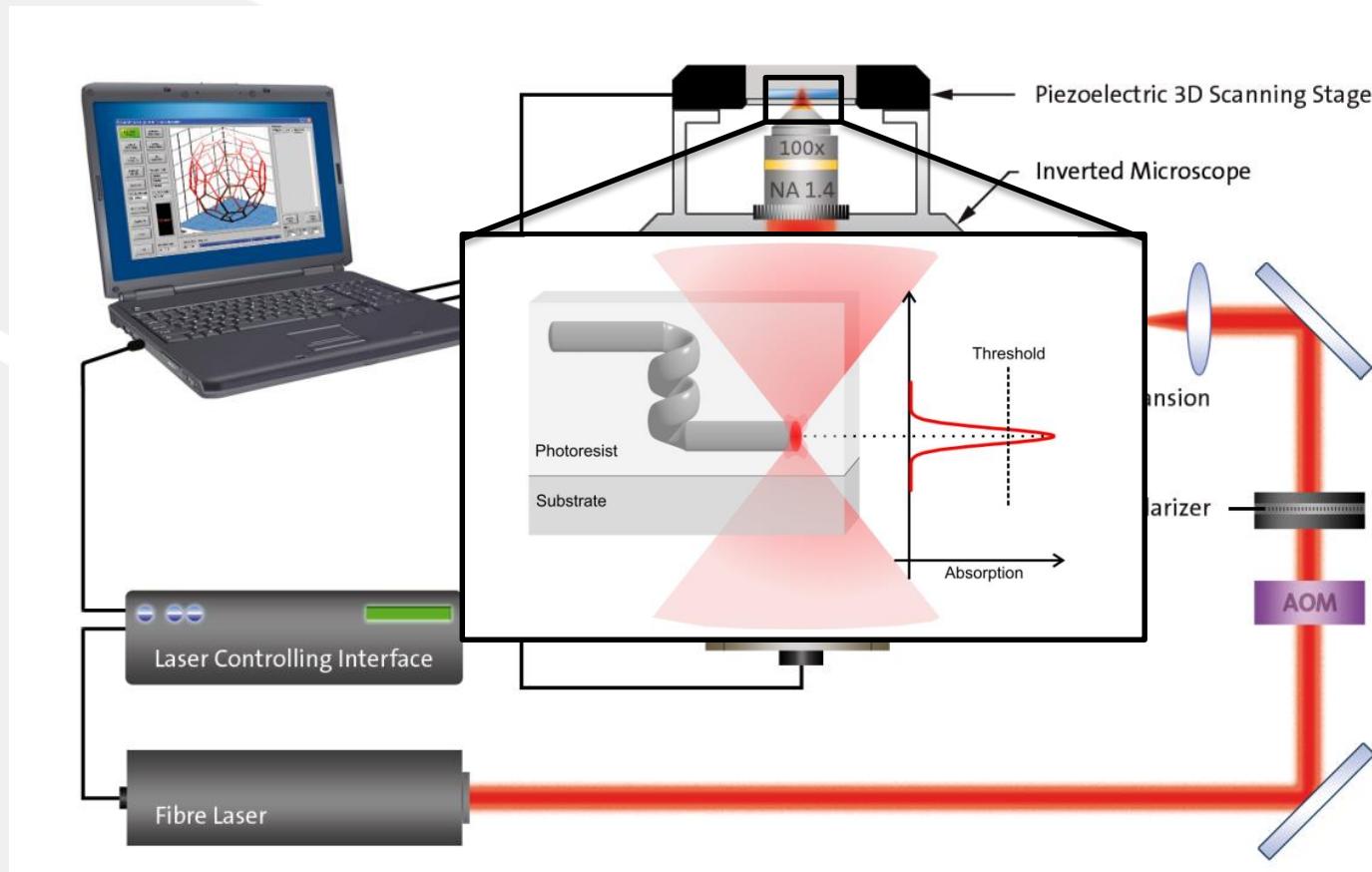
Photonic Professional GT





nanoscribe

3D Printing by Direct Laser Writing



Two-photon polymerization (TPP):

- Near-infrared laser
- Ultra-short laser pulses
- UV-curable photoresists



nanoscribe

3D Printing Workflow

1. Preparation

CAD-Design



 DeScribe
Mesh fixing
Slicing
Hatching

2. Production



NanoWrite
Print job controlling

Photonic Professional GT

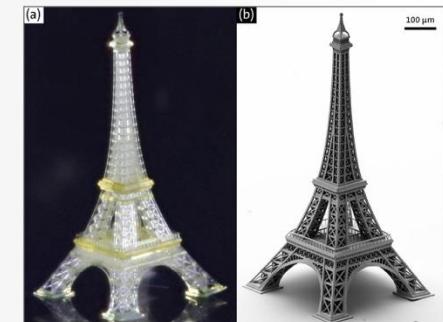


3. Post-Processing



Finishing

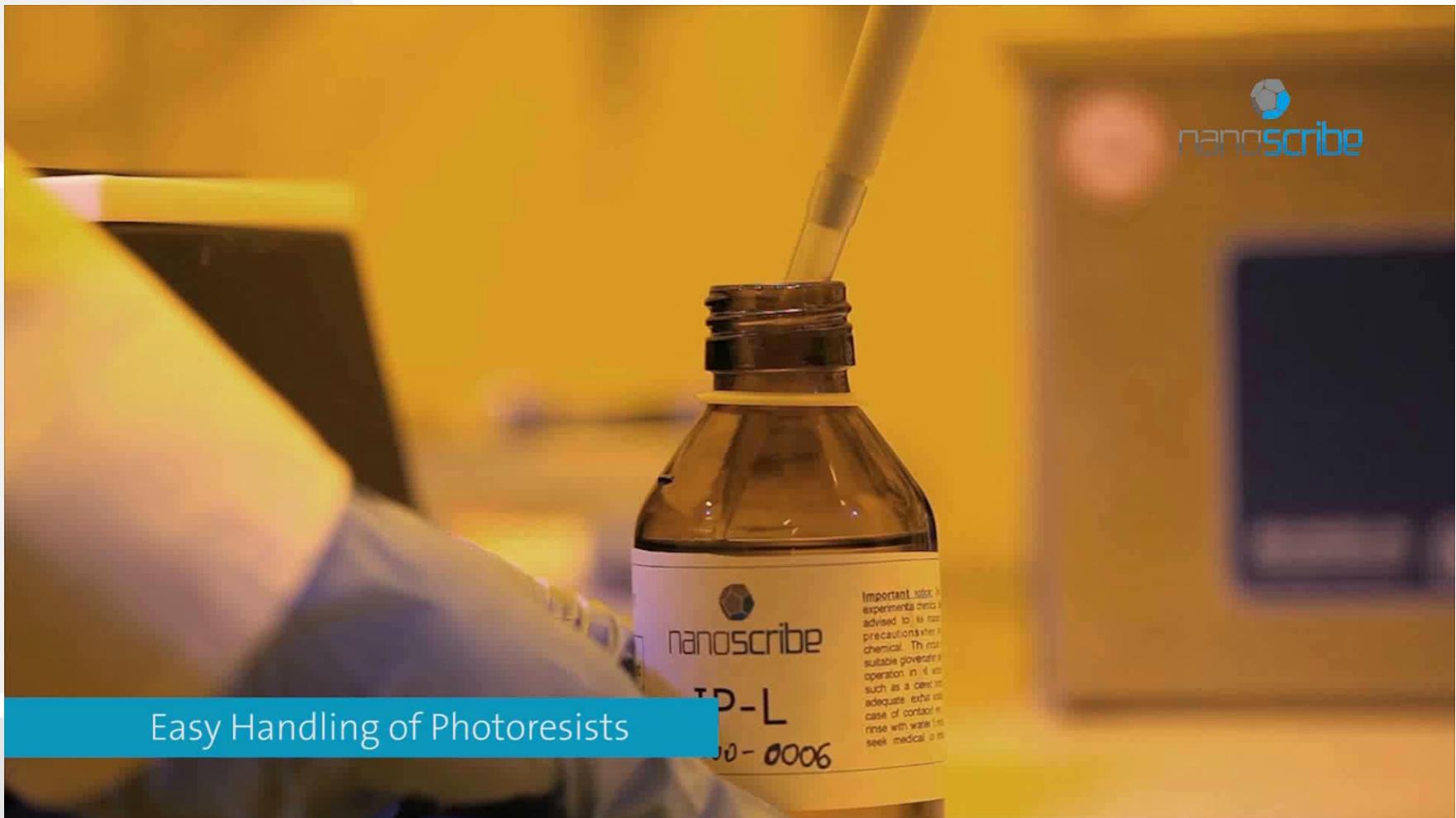
Removal of excess resin
Visual quality control





nanoscribe

Easy Workflow



Easy Handling of Photoresists



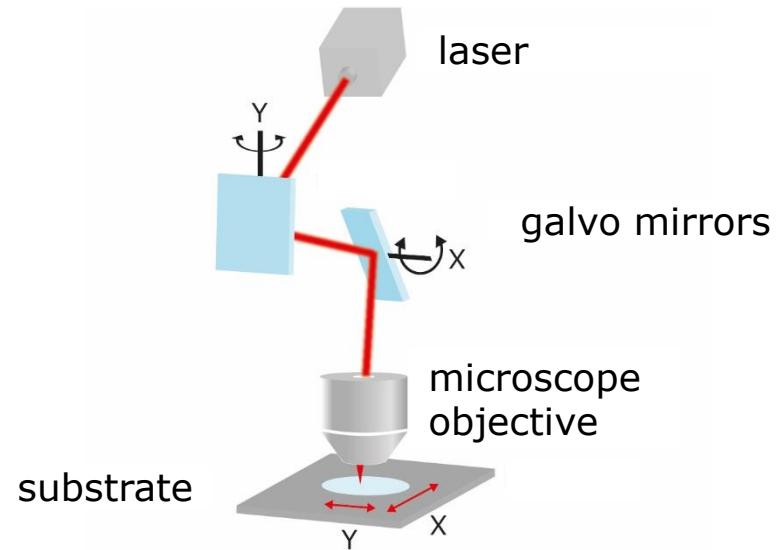
Embedded Writing Modes

Piezo mode



- Fixed laser focus
- Moving sample by piezoelectric stage
- 3-axes x-y-z-movement
- Arbitrary 3-dimensional trajectories

Galvo mode



- Deflection of laser focus by galvo mirrors
- Lateral movement in x-y-plane
- High-speed in-plane laser focus movement

Real-time Printing Process



nanoscribe



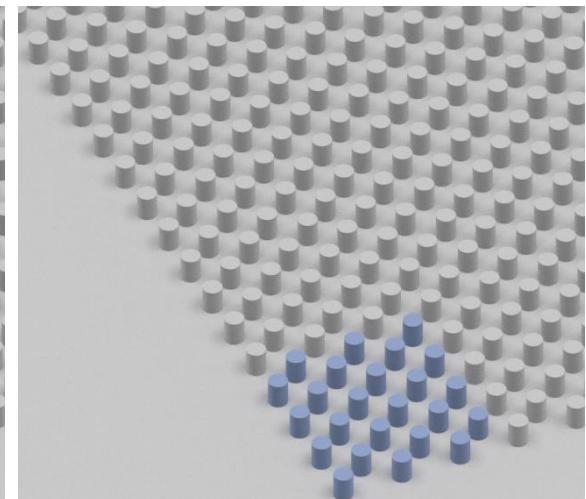
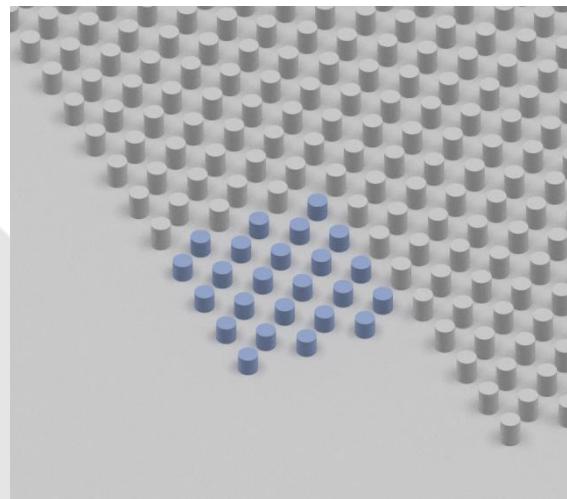
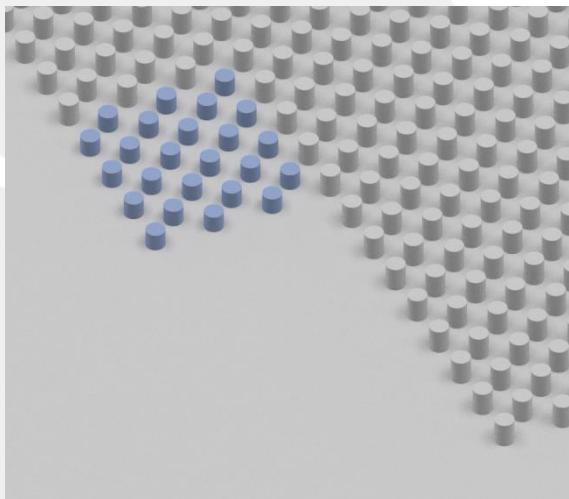
Application Video: 3D μ -Printing



nanoscribe

Large Area

Stitching of micro-structured arrays

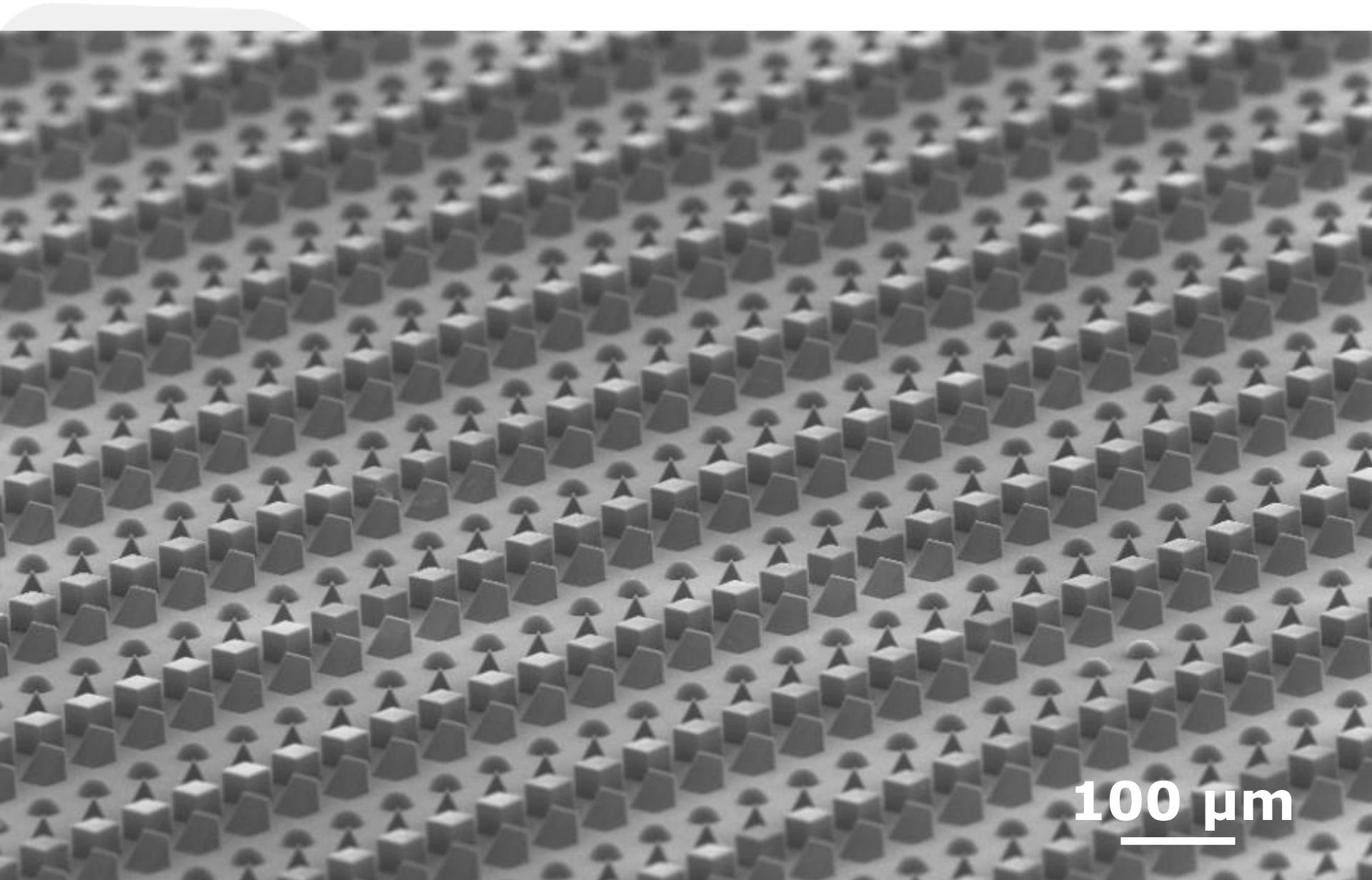


area ~2 cm²



nanoscribe

2.5D Micro-optics over large areas

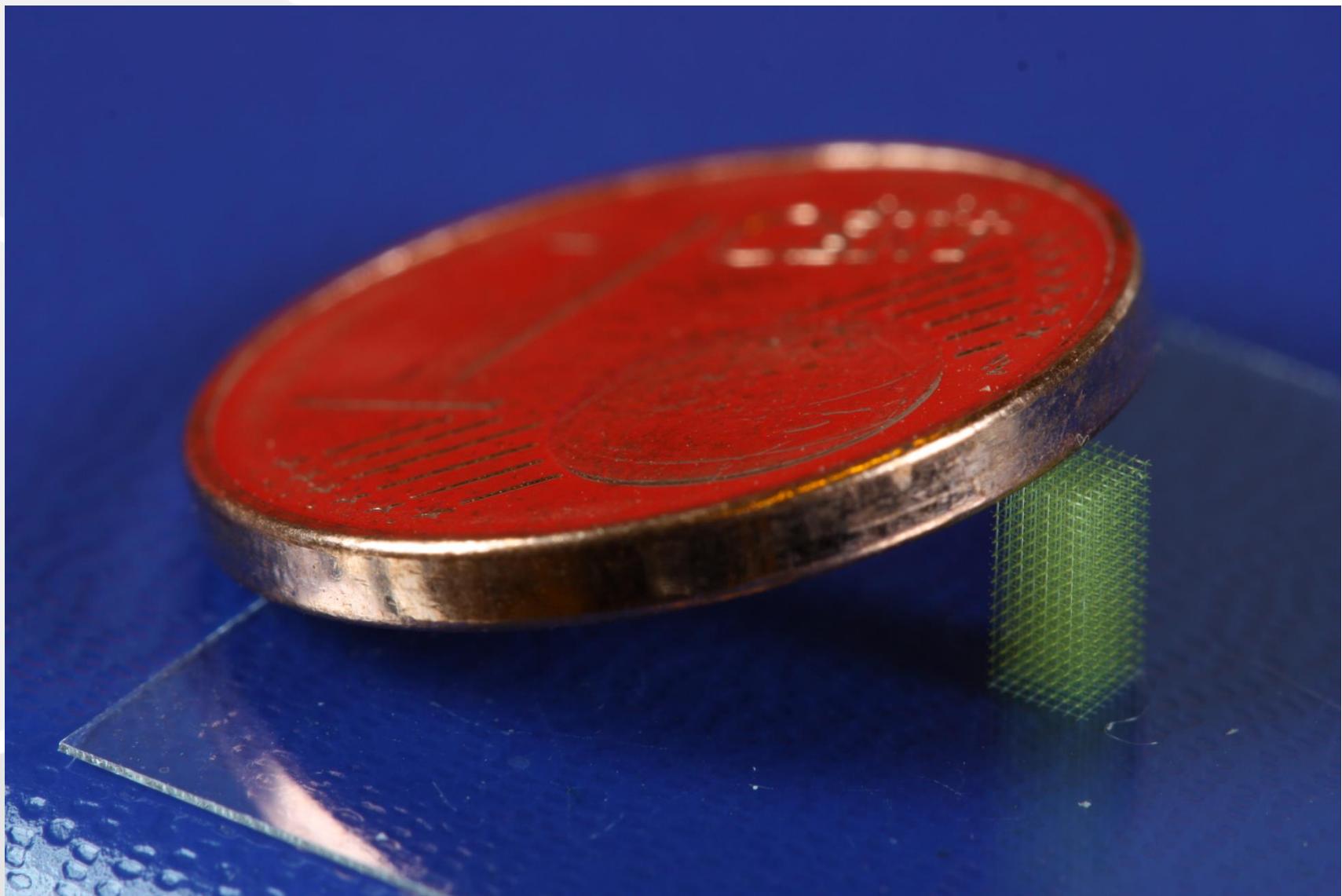


100 μm



nanoscribe

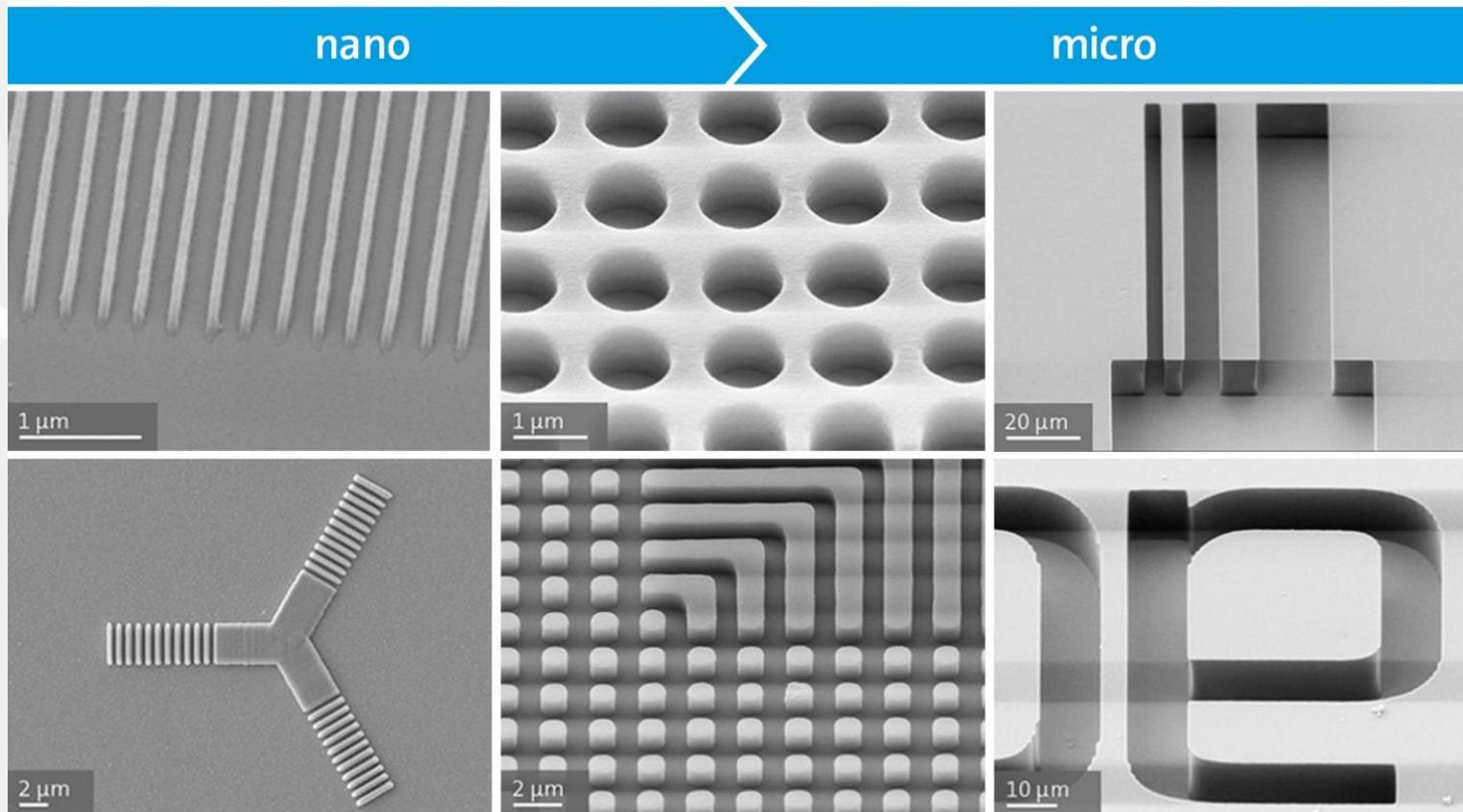
Meso-scaled parts





nanscribe

Maskless Lithography



2D & 2.5D: Maskless lithography – beyond UV- and grayscale lithography

- Design freedom at will (2.5D)
- Ultra-high aspect ratios (2D)
- Resolution: Bridging the gap between e-beam and UV-lithography



nanoscribe

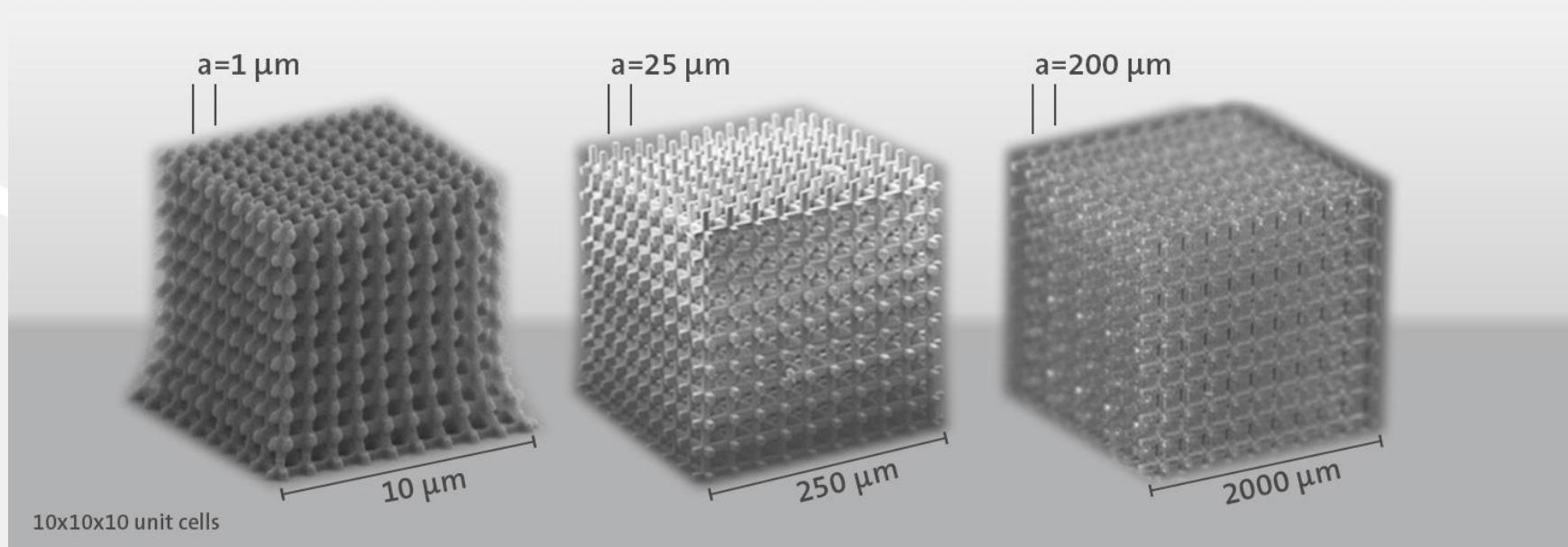
3D Printing

nano

micro

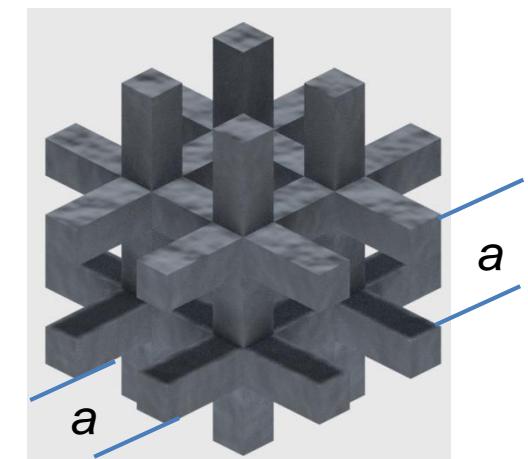
meso

macro



3D: Additive manufacturing along 3D Print Workflow

- Highest resolution 3D printer:
Feature sizes down to 200 nm
- Multi-scale: nm, μm and mm sizes
- High-speed fabrication
- Simple workflow





Overview

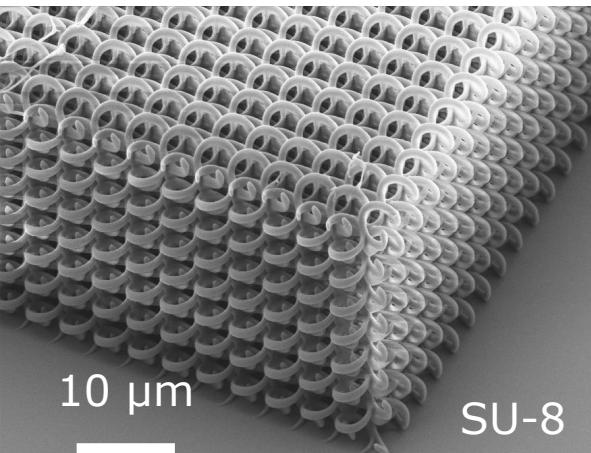
- Introduction: Nanoscribe GmbH
- Technology: Direct Laser Writing
- Materials
- Applications
- Summary





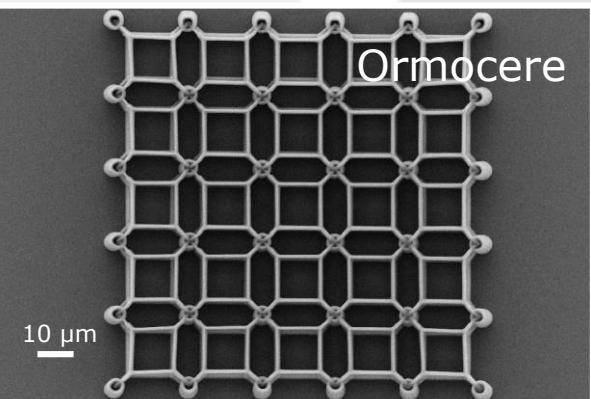
nanoscribe

Materials – Printable Resins

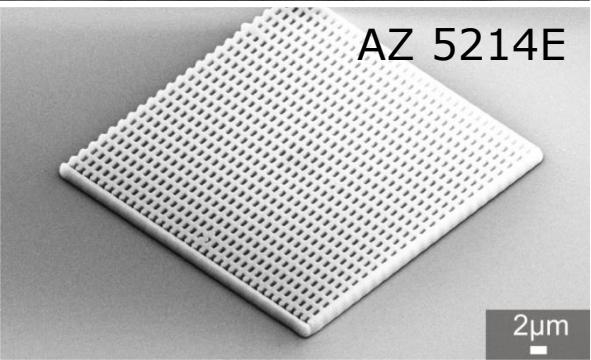


10 μm

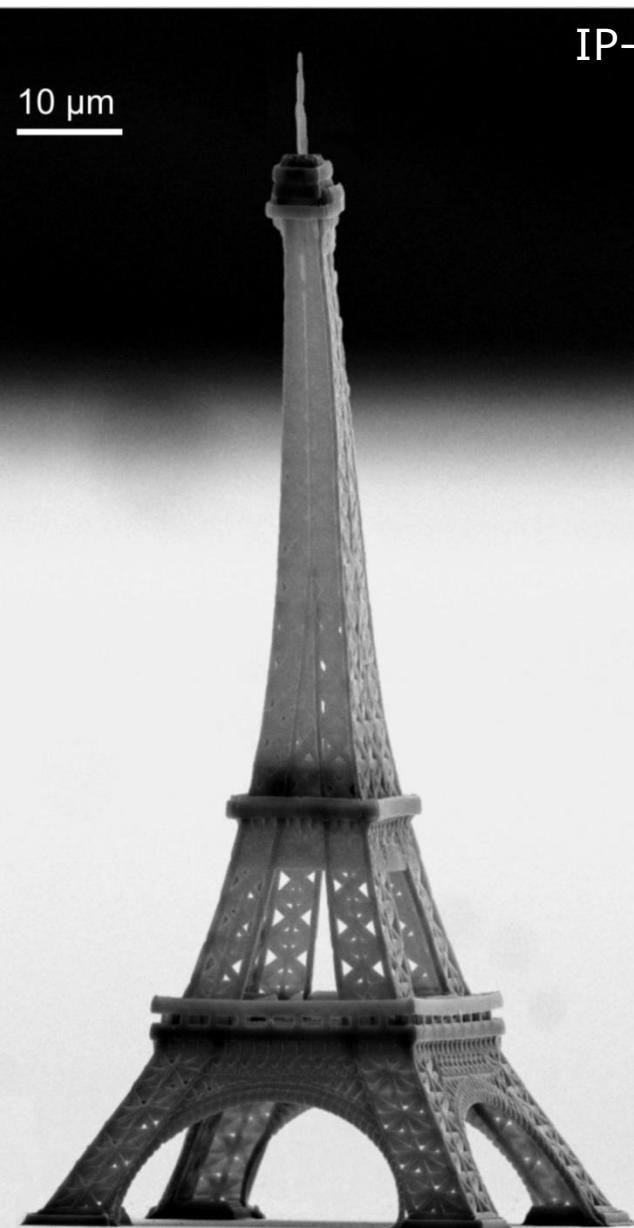
SU-8



Ormocere

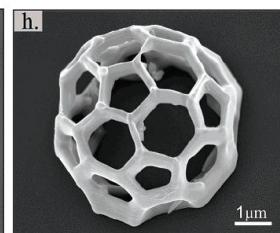
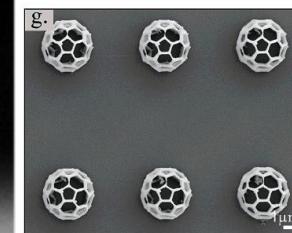
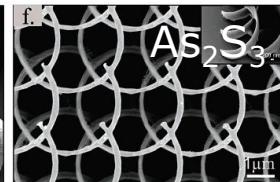
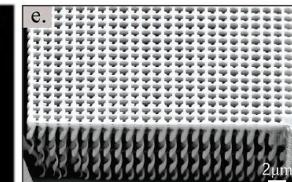
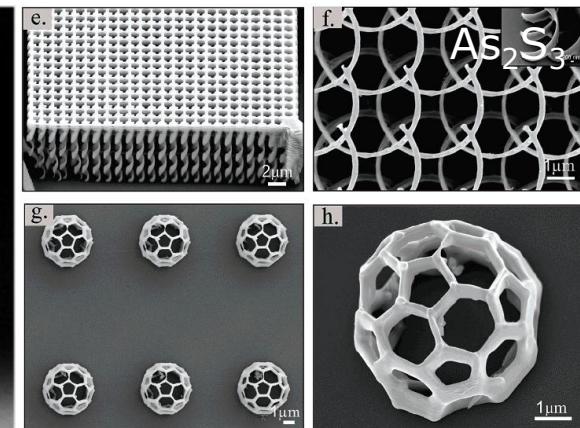


AZ 5214E

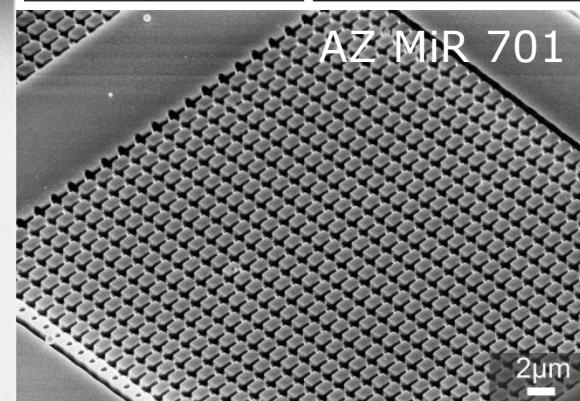


10 μm

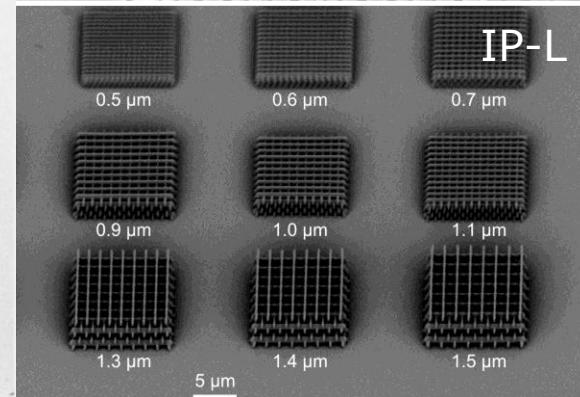
IP-G



AZ MiR 701



2μm



IP-L

0.5 μm

0.6 μm

0.7 μm

0.9 μm

1.0 μm

1.1 μm

1.3 μm

1.4 μm

1.5 μm

5 μm



nanscribe

Nanoscribe's IP-resists





Beyond IP-resists

- Photoresists from other suppliers:
 - Negative-tone: Ormocomp, SU-8
 - Positive-tone: AZ MIR 701, AZ 9260, AZ 5214, AZ 40XT
- Hydrogels: PEG-based hydrogels, BSA protein hydrogel,...
- Chalcogenide glass with high refractive index: As_2S_3
- Polymer mixture: IP-resin with...
 - Nanoparticles (rare-earth doped for temperature measures)
 - Ionic liquids (Conductive composites for sensing applications)
- Liquid crystal elastomers (LCE; light-actuated microtools)

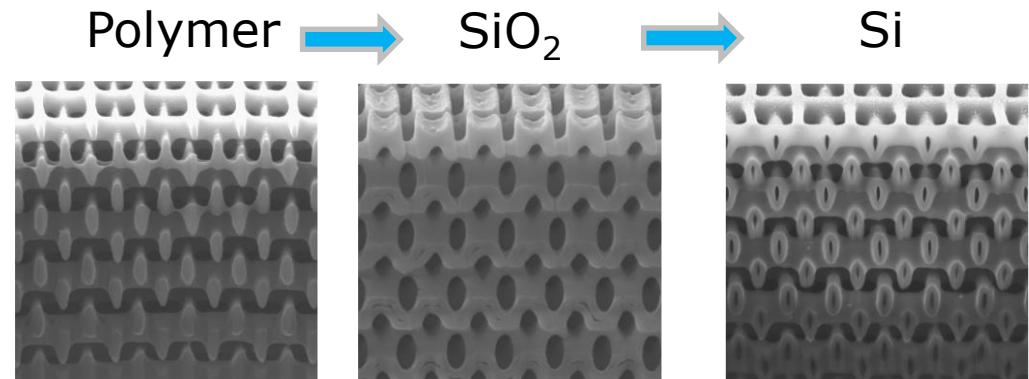


nanoscribe

Materials – Casting from Polymers

Dielectrics:

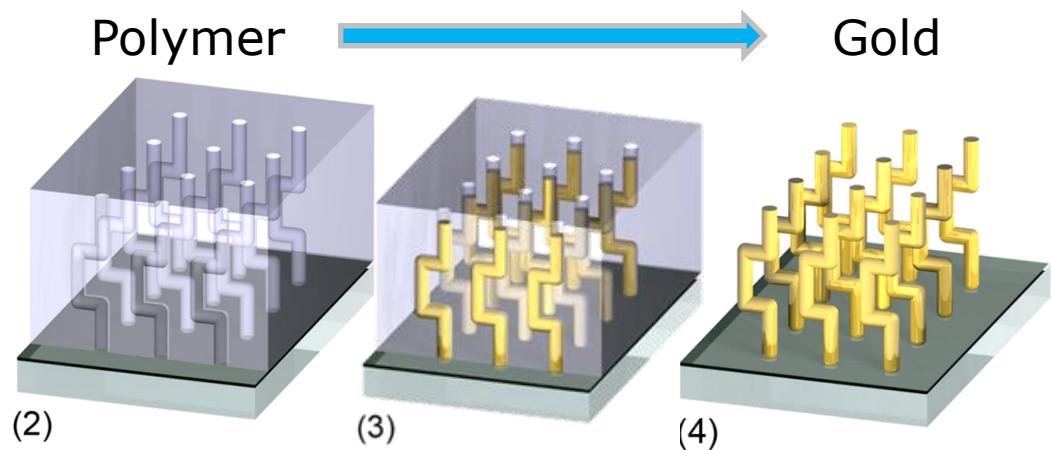
- Silicon Chemical Vapor Deposition (CVD)
- Silica Pulsed Layer Deposition (PLD)
- Titania Atomic Layer Deposition (ALD)



M. Hermatschweiler *et al.*, Adv. Funct. Mater. **17**, 2273 (2007)

Metals:

- Gold Electroplating / Galvanization
- Silver Chemical Vapor Deposition (CVD)



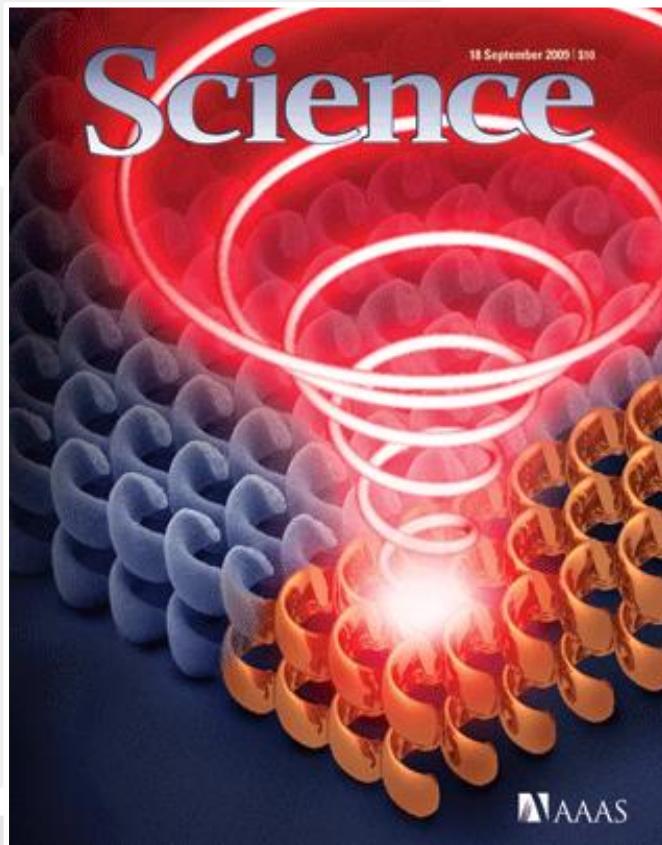
J. Gansel *et al.*, Science **325**, 1513 (2009)



nanoscribe

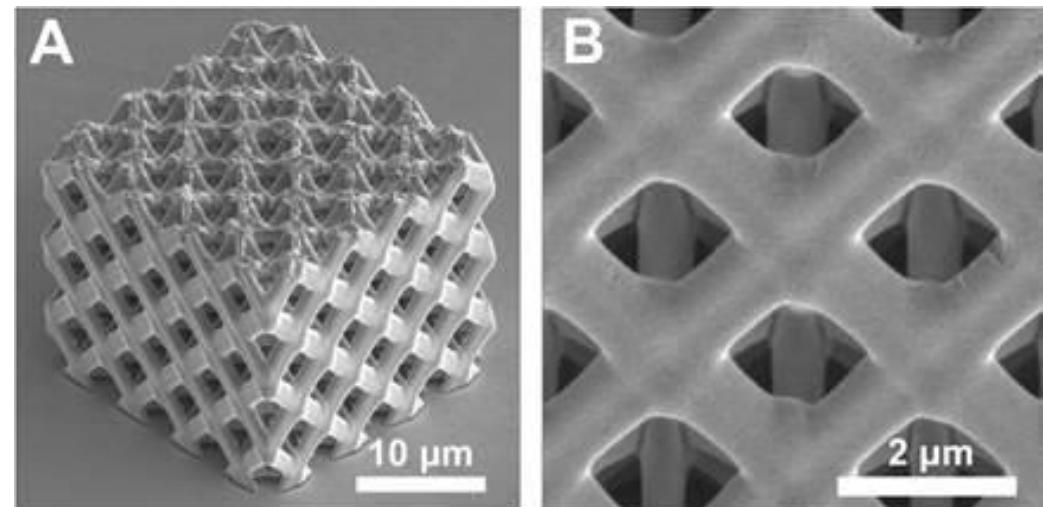
Casting from Polymers

Gold helical photonic
metamaterials



J. Gansel et al., Science **325**, 1513
(2009)

Ultra-strong Copper Mesolattices



X. Wendy Gu et al., [Extreme Mechanics Letters, 0, 2352 \(2015\)](https://doi.org/10.1016/j.eml.2015.01.006), DOI:
[10.1016/j.eml.2015.01.006](https://doi.org/10.1016/j.eml.2015.01.006)

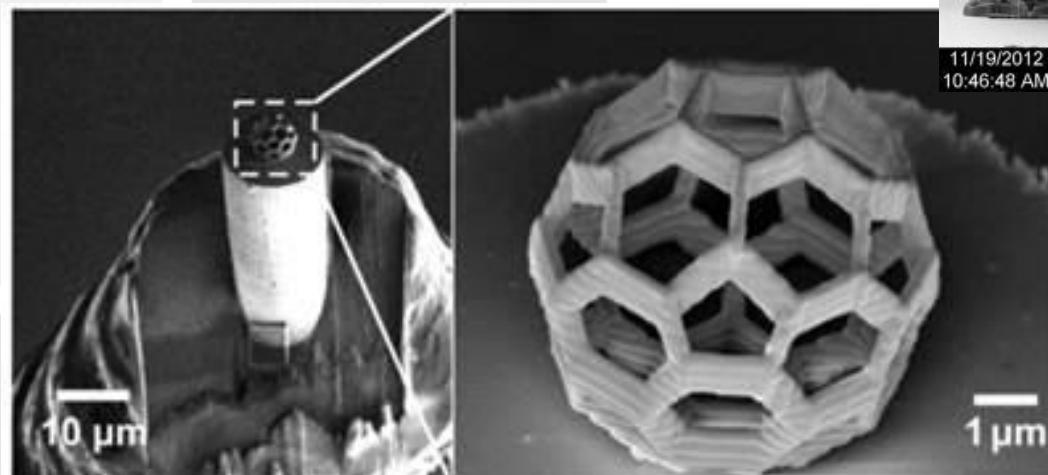
Coating

Stability tests of plant-like designed scaffolds:

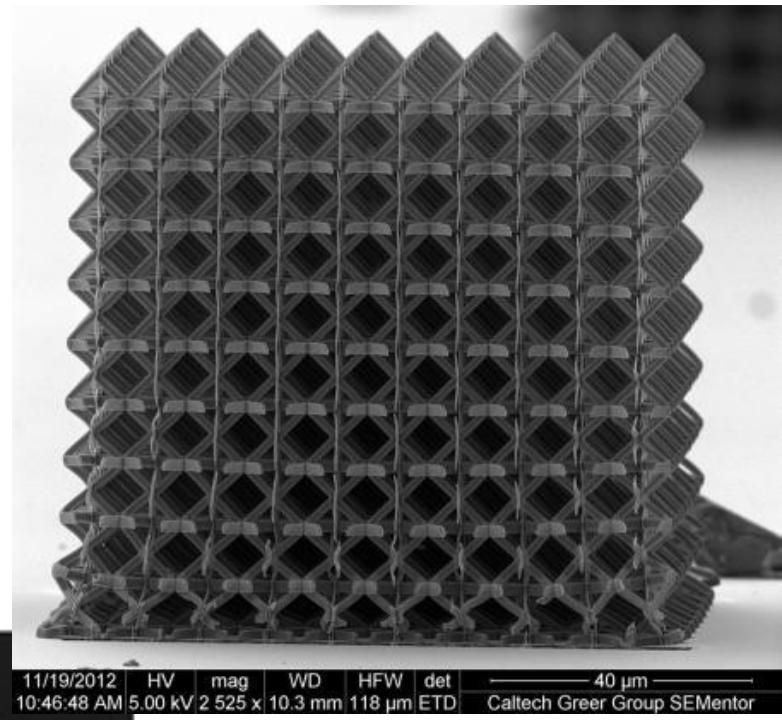
- Casting to titanium nitride (TiN) by ALD; deformation tests with hollow ceramic structures

Testsample for x-ray phase Tomography:

- 3D sample coated with Co



Claire Donnelly et al., Phys. Rev. Lett. 114, 115501 (2015);
DOI: 10.1103/PhysRevLett.114.115501



J. R. Greer et al.,
Nature Materials **12**, 893 (2013)

Metals, Semiconductors, Ceramics...



Subsequent processing via ALD, CVD, electroless plating, galvanization, etc. allows for transfer into different materials:

- Cu, Ag, Au
- Ni, Co
- GaAs, Si
- SiO_2
- Ti, TiO_2
- TiN, Al_2O_3
- ...

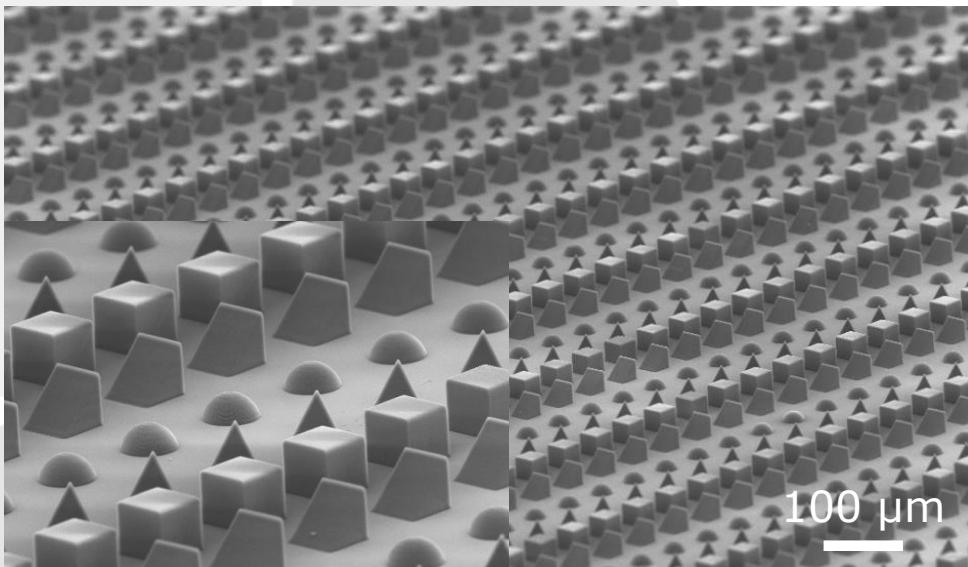
See: <http://www.nanoscribe.de/en/media-press/scientific-articles/>



nanoscribe

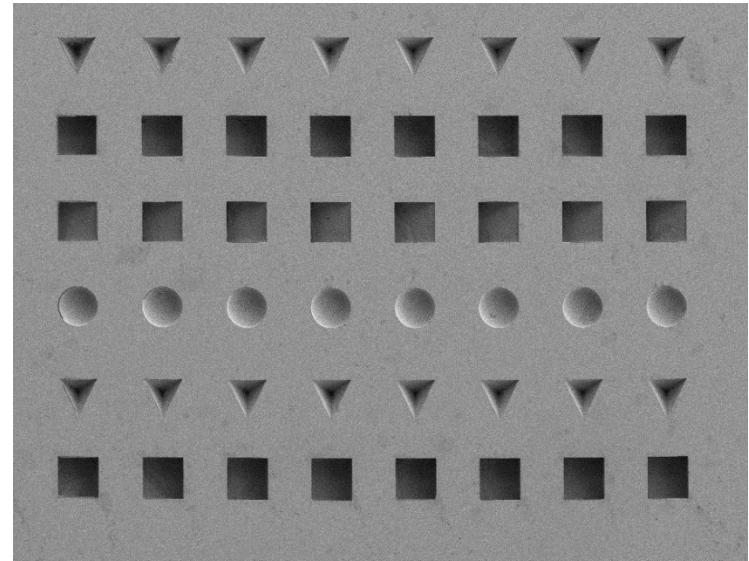
LIGA compatible in all dimensions

- Partners for electroplating:
 - Mimotec SA
 - microworks GmbH
 - Eleoss GmbH
- Serving as masters for:
 - Injection molding
 - Nanoimprint



MASSMICRO

Nickel shim by microworks



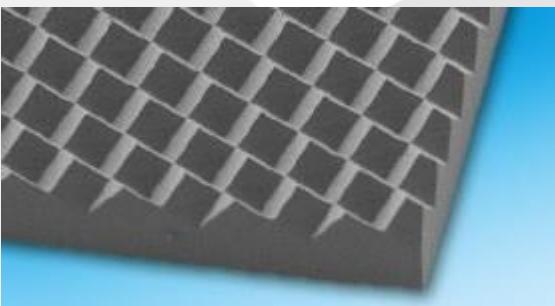


nanoscribe

Applications



Scaffolds for Cells



Micro-optics



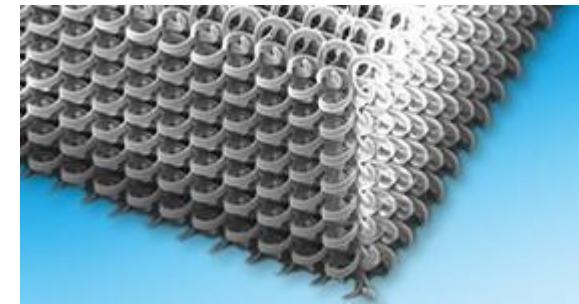
Microfluidics



Photonic Wire Bonding
Optical Integration



MEMS



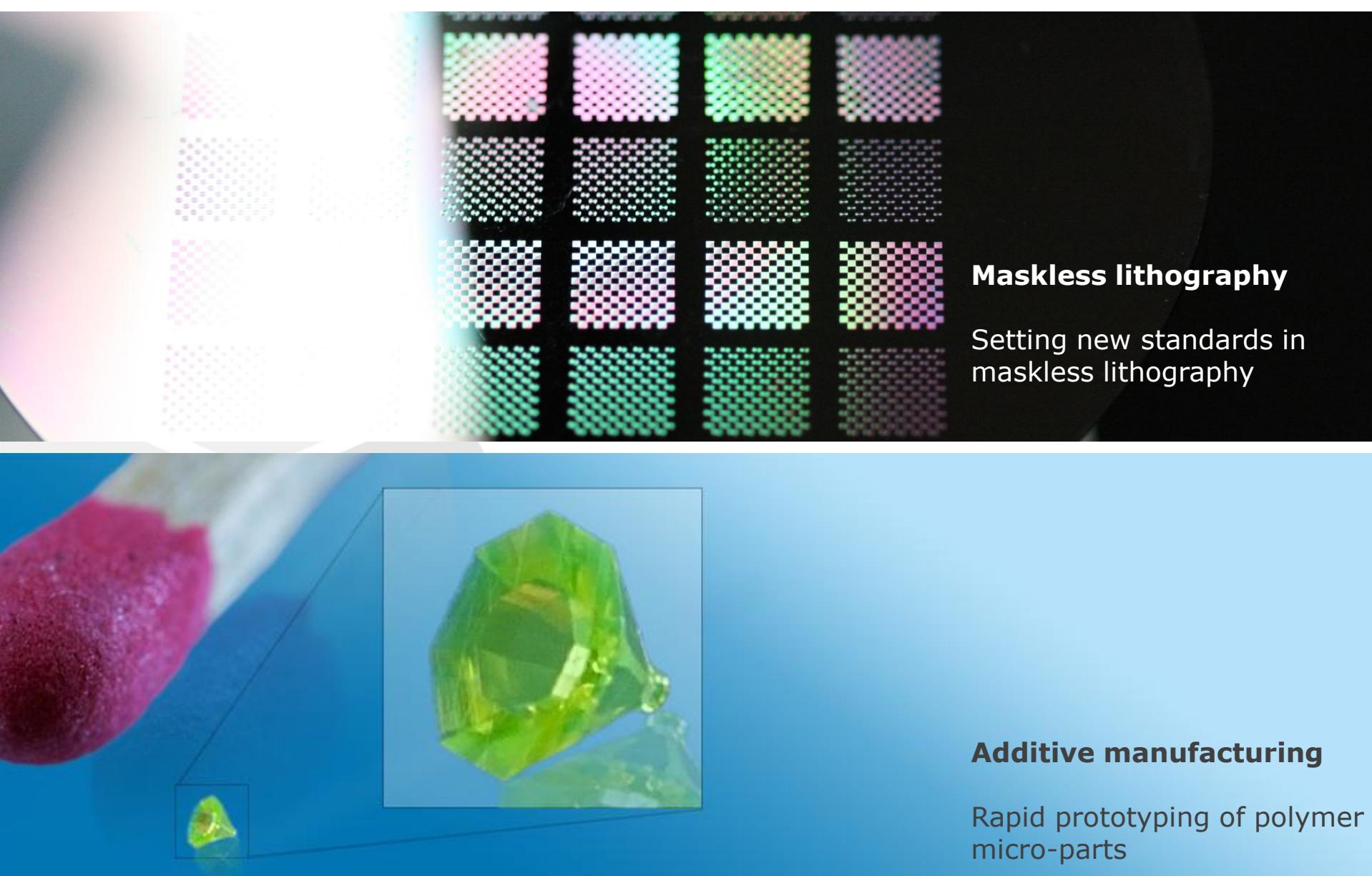
3D Photonics



Maskless Lithography



Rapid Prototyping



Maskless lithography

Setting new standards in
maskless lithography

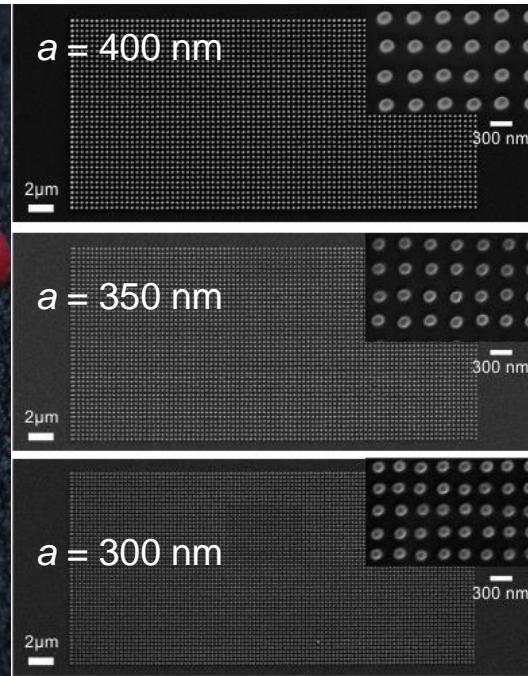
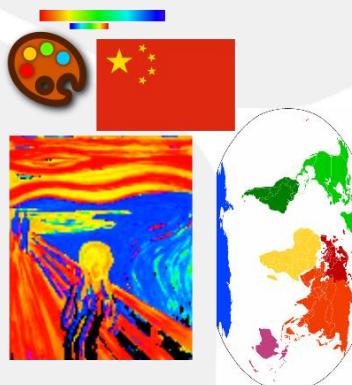
Additive manufacturing

Rapid prototyping of polymer
micro-parts

Applications – Maskless Lithography

Photonic Colors / Security Labels

Graphical Input
(png, jpg,...)



Minimal lateral feature size down to 200 nm.

Nano-pillar array with periods of 600 nm to 1600 nm.



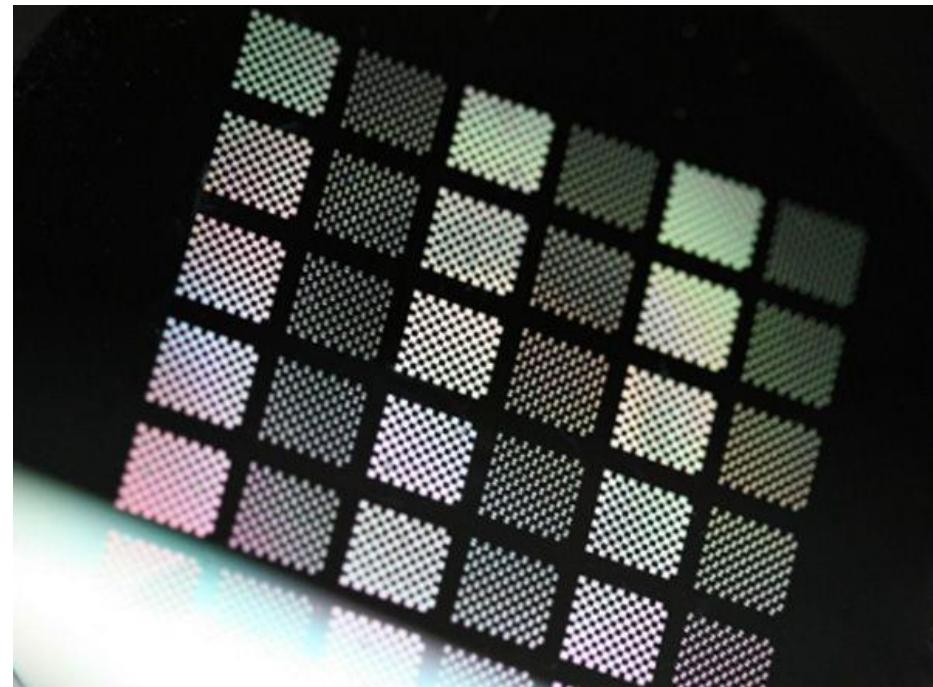
Maskless Lithography

Typical negative tone resists:

- SU-8 (MicroChem)
- IP-Resists (Nanoscribe)

Positive tone resists:

- AZ 9260
- AZ MIR 701
- AZ 5214
- AZ 40XT

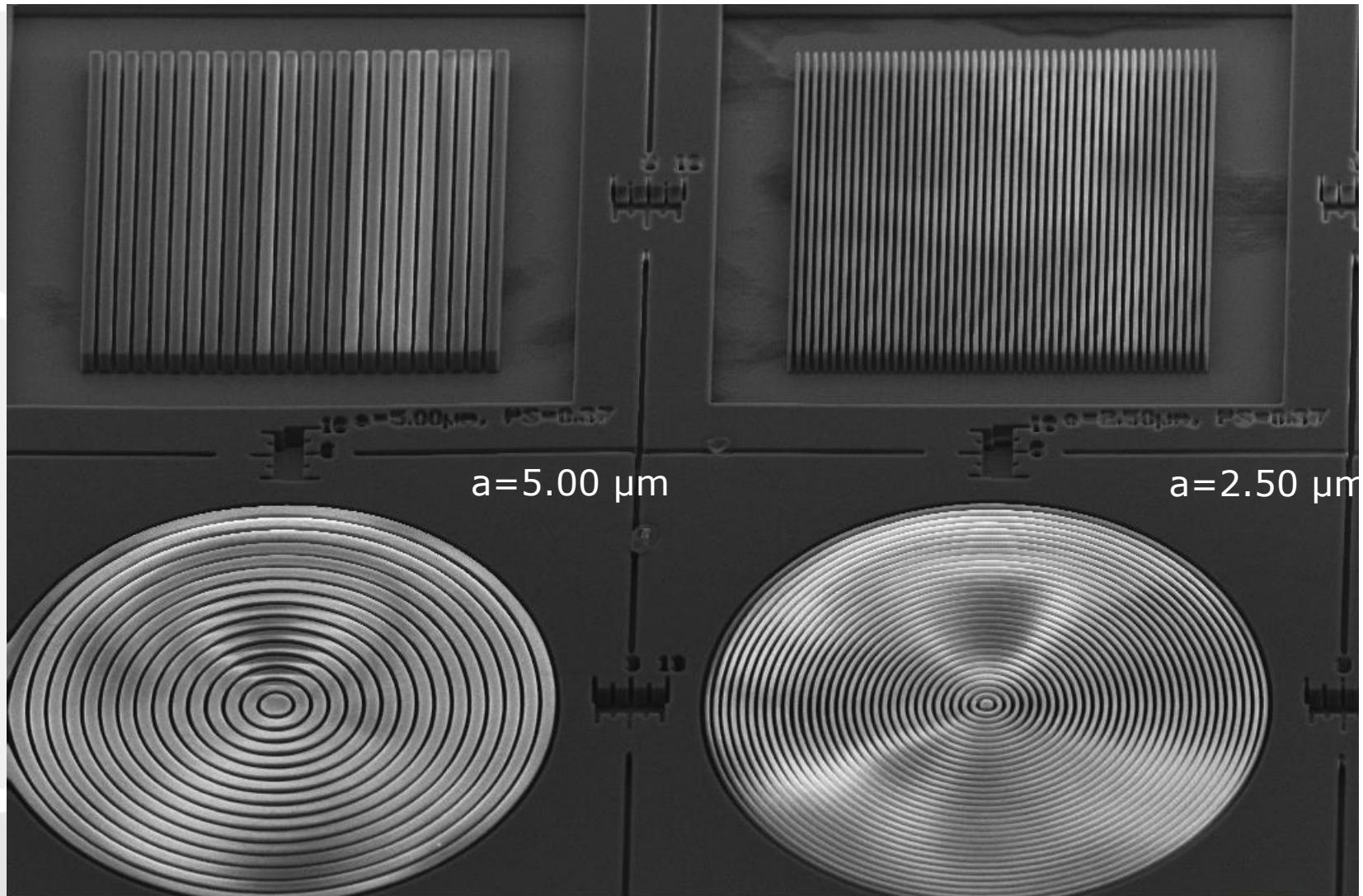


4" wafer with patterned positive tone resist



nanoscribe

Positive Tone Resist Test Patterns



Stage at T = 45.0 °
Mag = 300 X

EHT = 10.00 kV
WD = 15.6 mm

Signal A = SE2
File Name = SN646_0066_48.tif

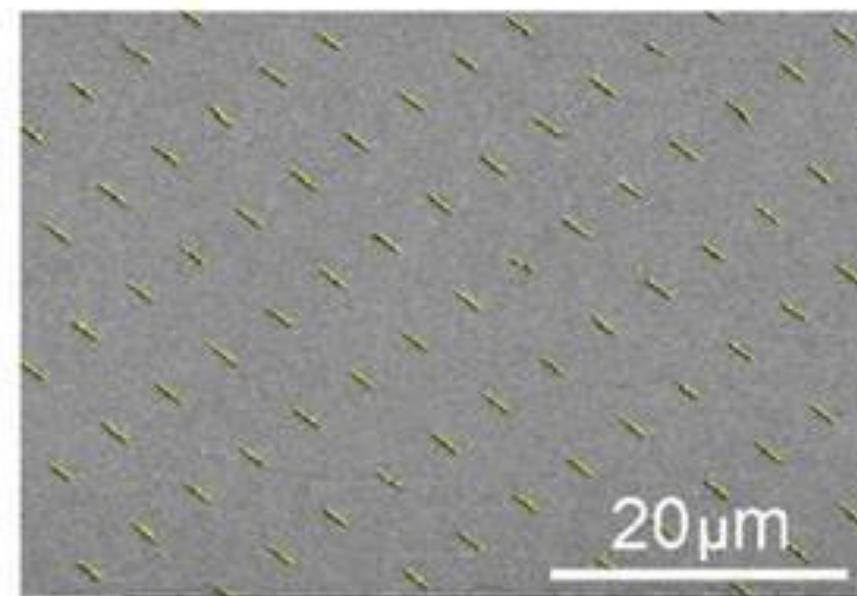
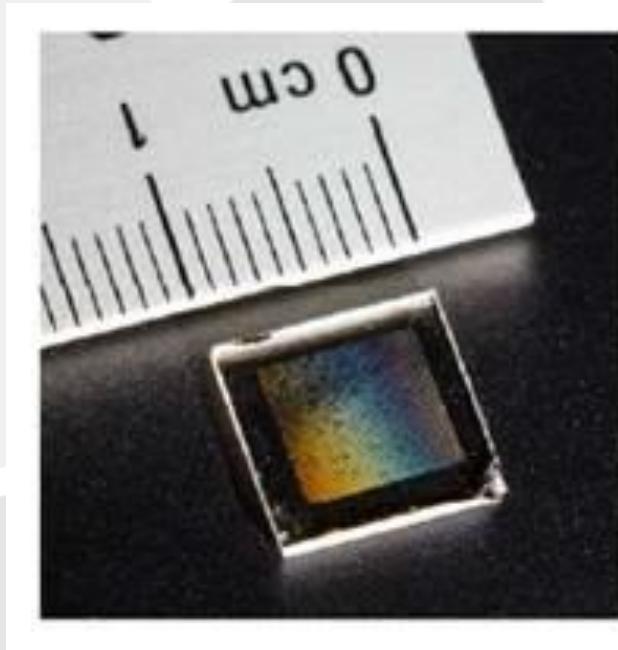
Date : 7 Nov 2013
Time : 17:10:17





Plasmonic cm² nanoantenna array

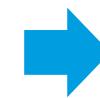
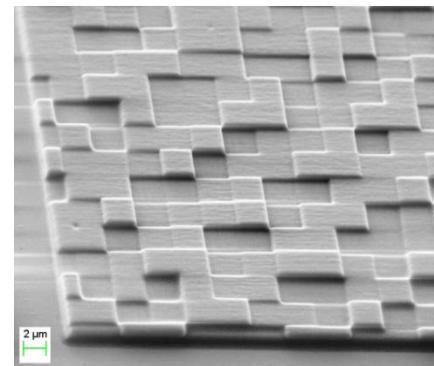
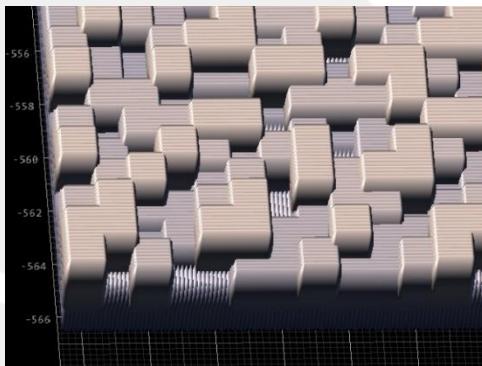
- Gold nanoantenna arrays for sensing applications
- Surface-enhanced infrared absorption (SEIRA).
- S. Bagheri et al. Fabrication of cm² plasmonic nanoantenna arrays by femtosecond direct laser writing lithography: Effects of collective excitations on SEIRA enhancement, ACS Photonics, [DOI:10.1012/acsphtnics5b00141](https://doi.org/10.1012/acsphtnics5b00141)



Optical Security Labels: n-level DOE



nanoscribe



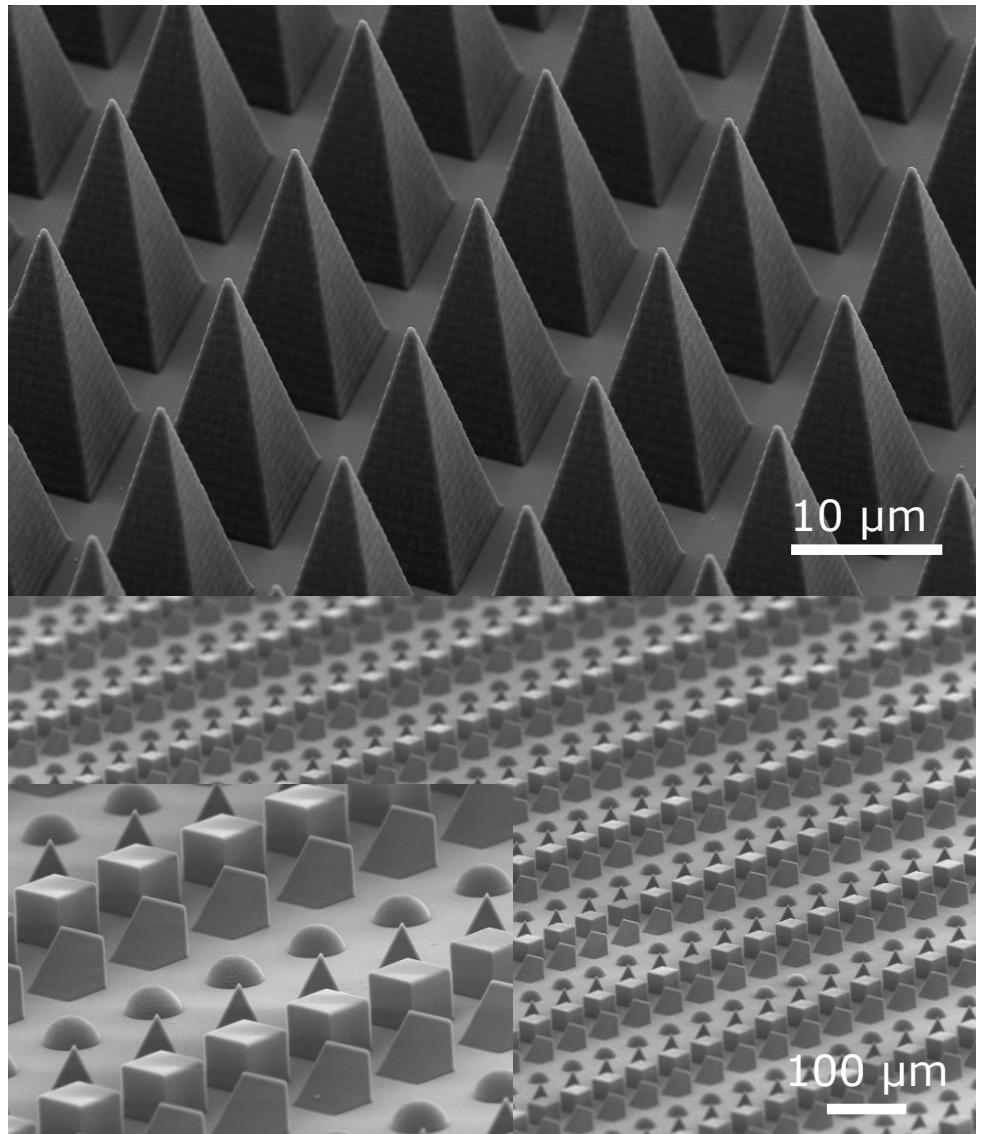
Product lifecycle leverage effects:

- **Removing process steps:**
 - 1 step instead of n steps
 - 1 printer instead of UV/e-beam + mask aligner
 - No spin-coater, no soft-bake, no hard-bake, just print!
- **Saving time & costs:**
 - 1 day instead of > 1 week
 - Less equipment
 - No masks!

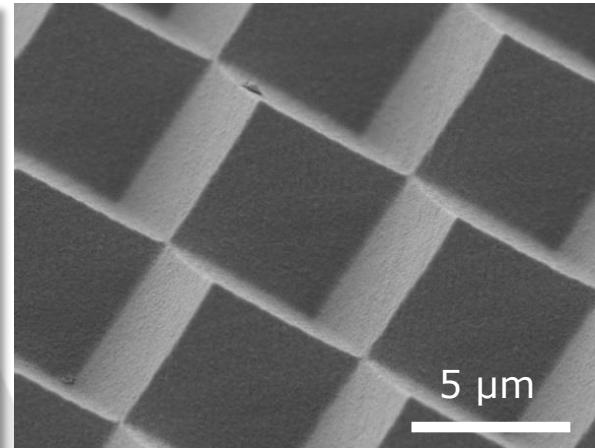
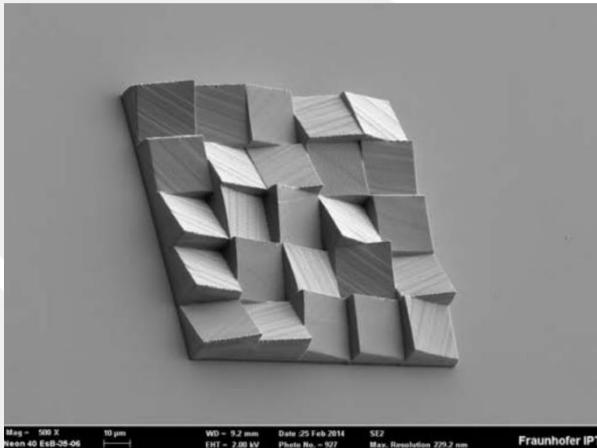


2.5D – Beyond Gray Scale Litho

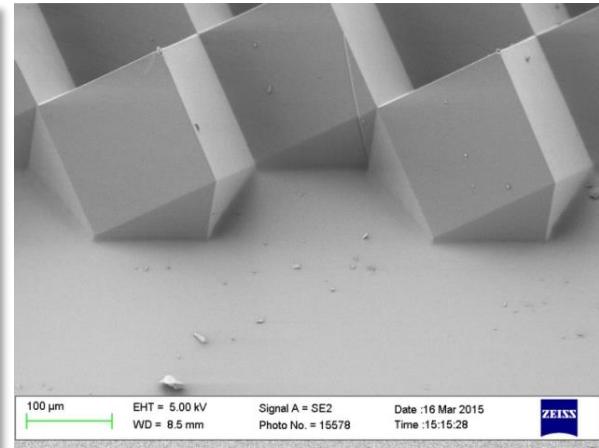
- Freedom of design
- Simple process for liquid resists
- Visual feedback
- High aspect-ratio



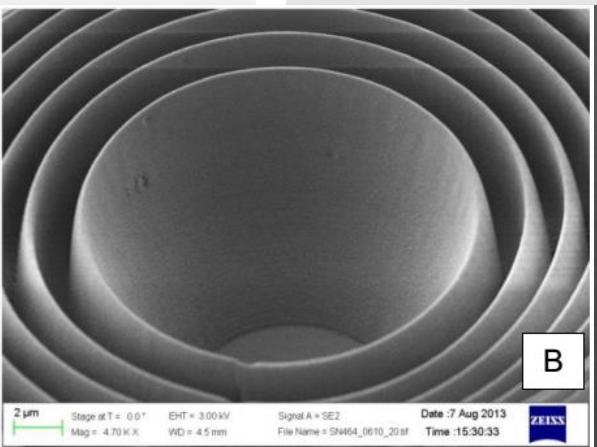
Microoptics



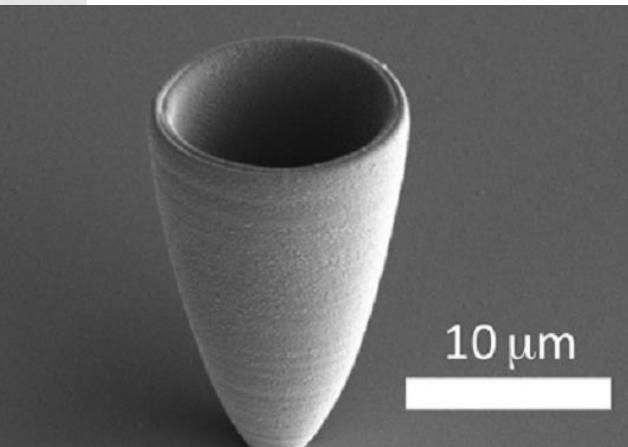
E. Harnisch *et al.*, Photonik 4 (2015) Retro-reflector



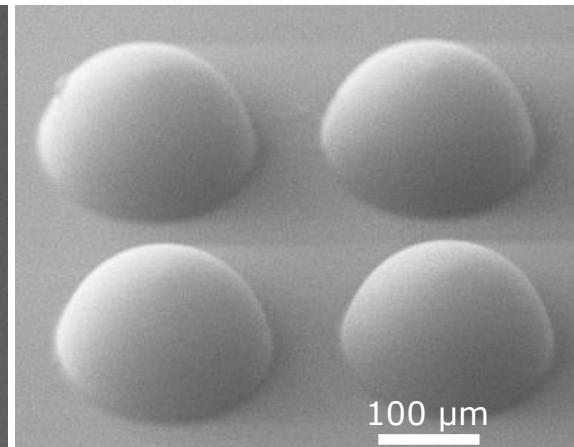
Cornercube retro-reflector



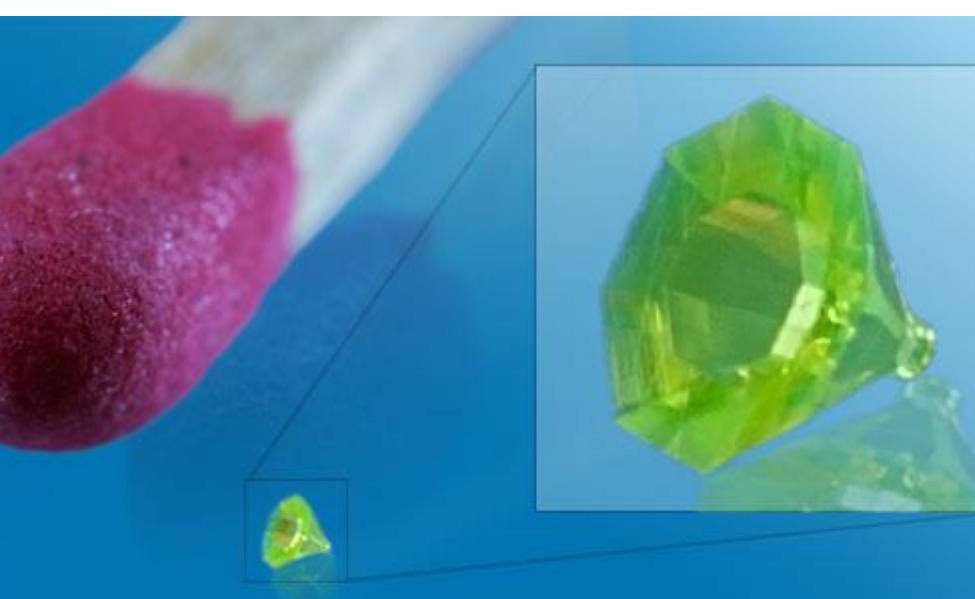
Fresnel lens



J. H. Atwater *et al.*, APL 99, 151113 (2011)

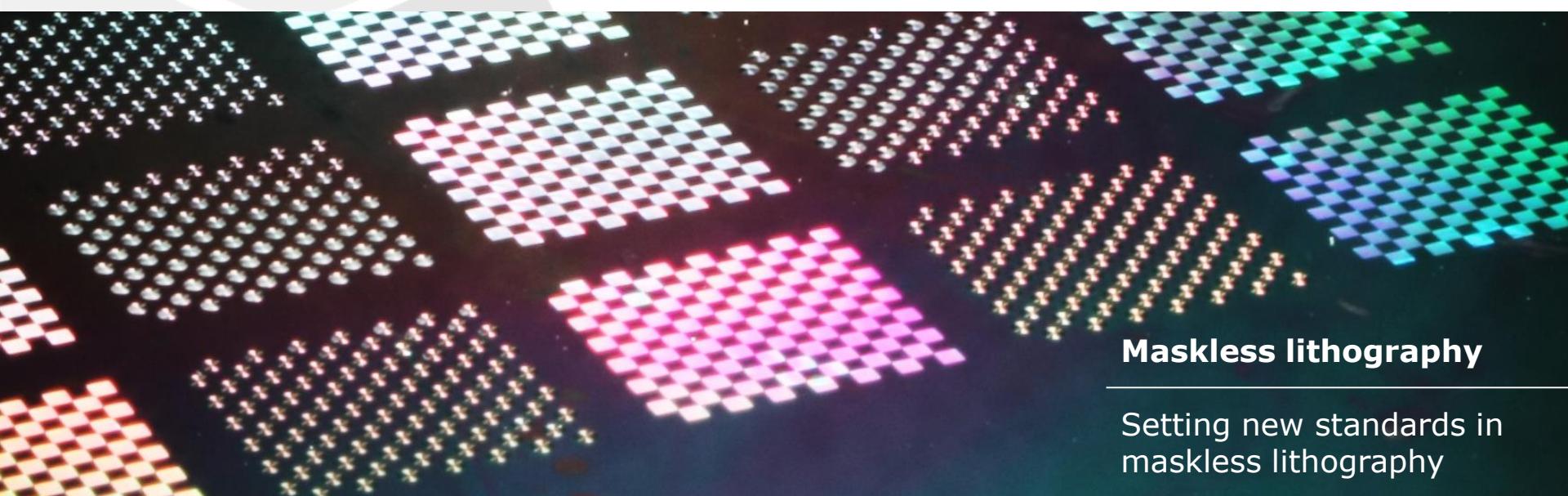


Half-spheres



Additive manufacturing

Rapid fabrication of
polymer micro-parts



Maskless lithography

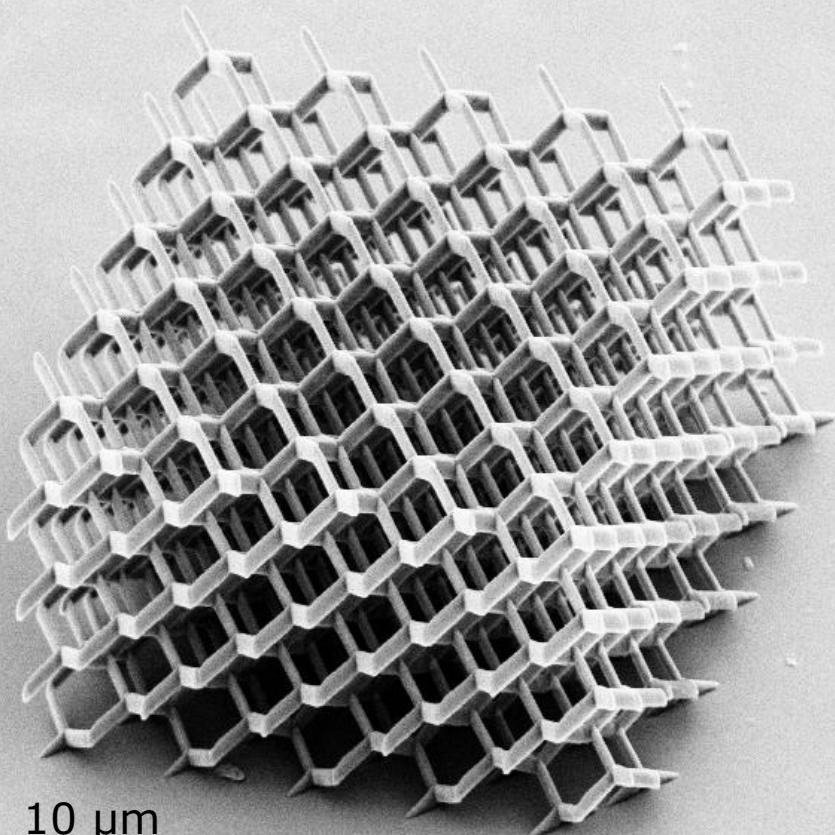
Setting new standards in
maskless lithography

Applications – Additive Manufacturing

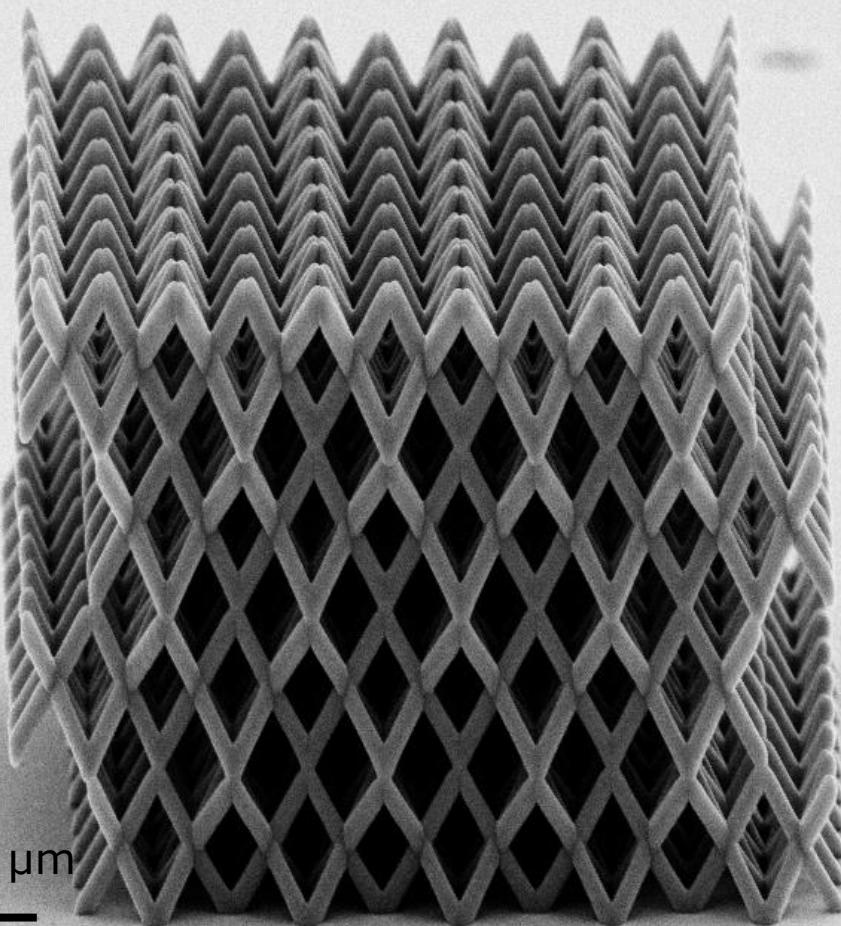


nanoscribe

3D Photonic Crystals



10 μm



2 μm

according to K. Edagawa *et al.*, PRL 100, 013901 (2008)

Design provided by ITMO, Russia



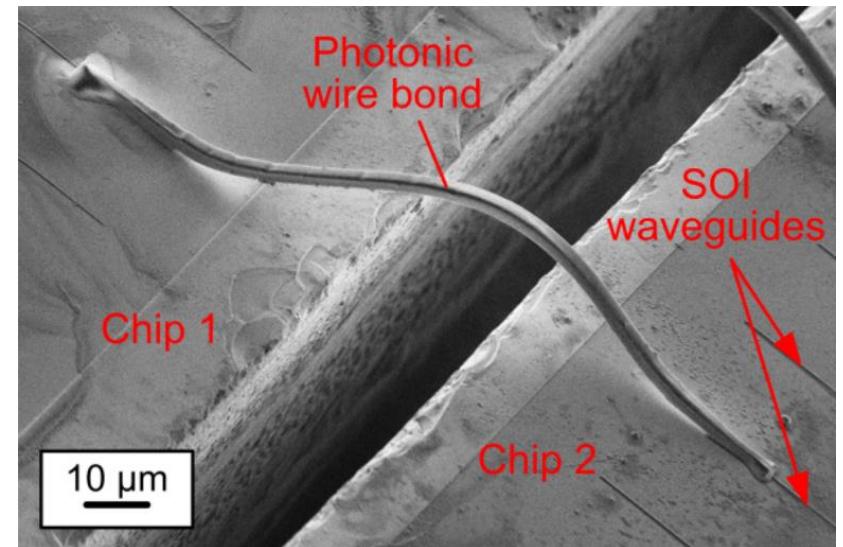
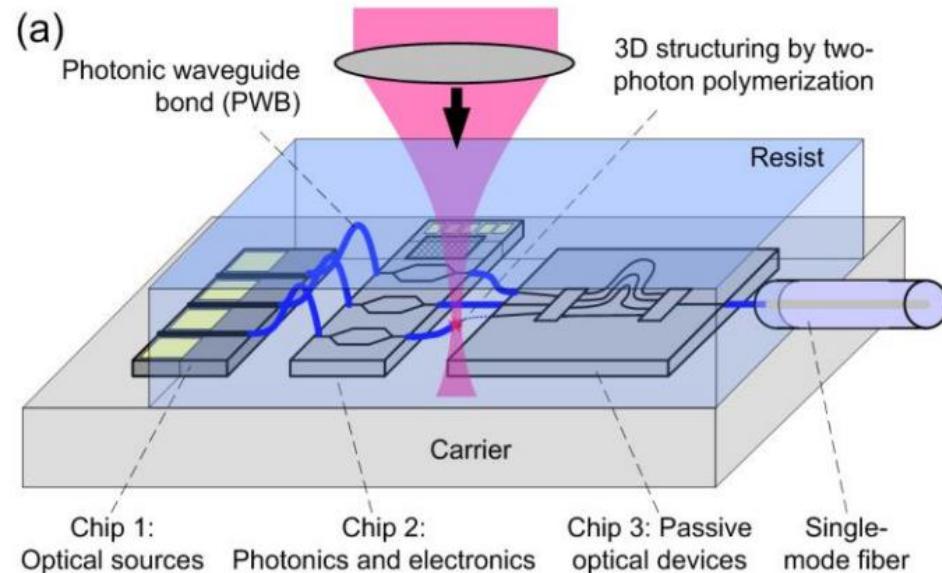
nanscribe

Photonic Waveguide Bonds

Optical Interconnects:

- Optical integration from chip-to-chip
- Optical analog to electrical wire bonds of electrically integrated circuits (IC)
- Data rates in information processing: >5 Tbit/sec
- BMBF funds project „Phoibos“
www.phoibos.de

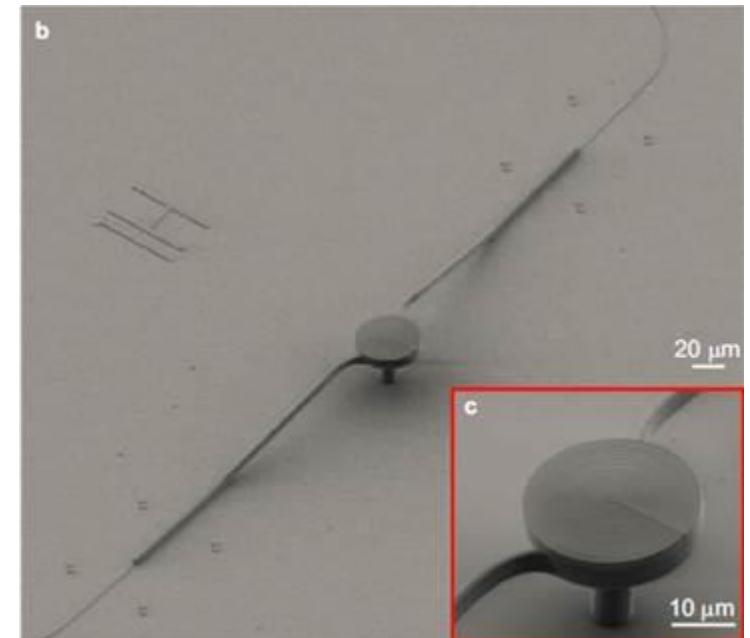
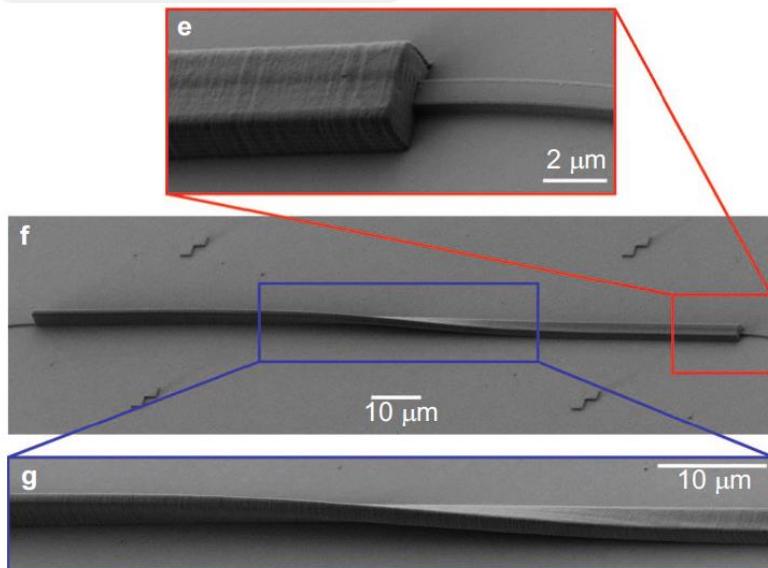
PHOIBOS



Optics Express, Vol. 20, 17667 (2012)

Integrated Optics

- Broadband polarization rotator connecting two nanophotonic waveguides
- Whispering-gallery-mode optical resonator connected to Si_3N_4 waveguides



M. Schumann et al; Light: Science & Applications (2014) 3, DOI:10.1038/lsa.2014.56

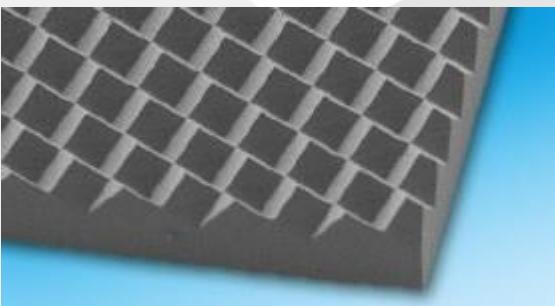


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Applications



Scaffolds for Cells



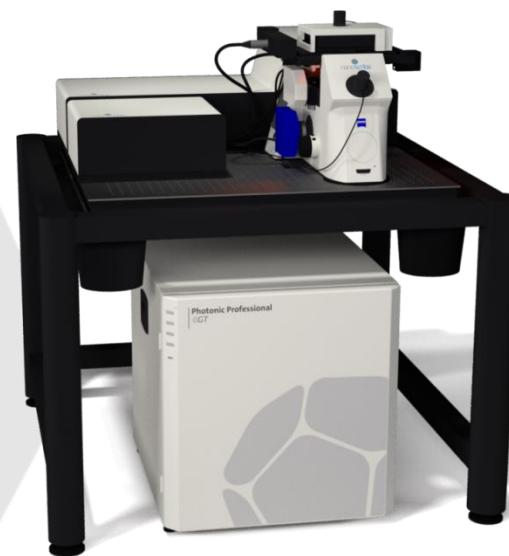
Micro-optics



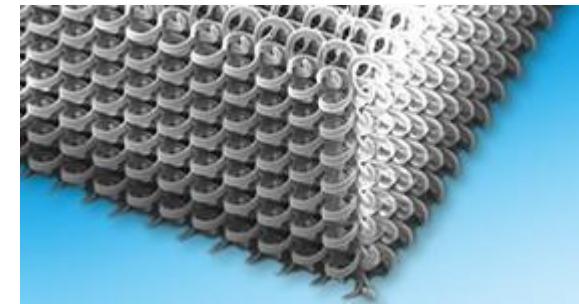
Microfluidics



Photonic Wire Bonding
Optical Integration



MEMS



3D Photonics



Maskless Lithography

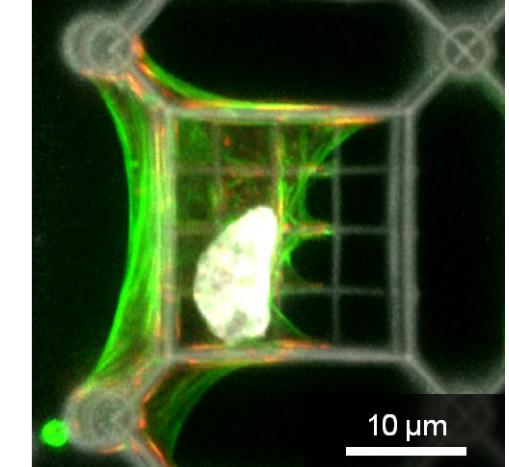
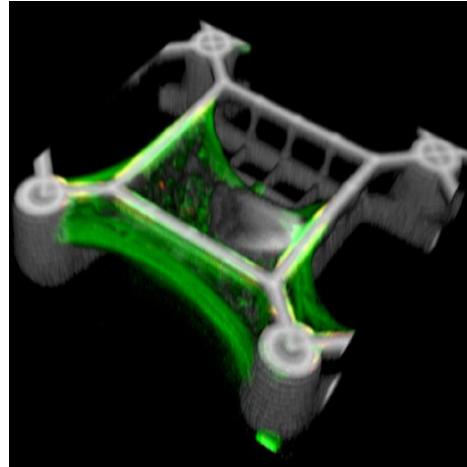
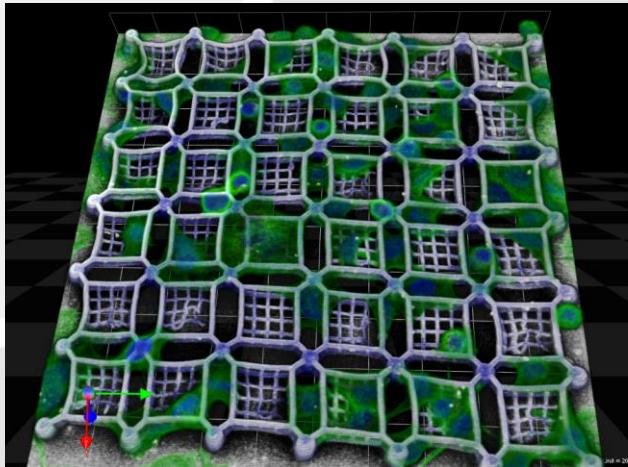
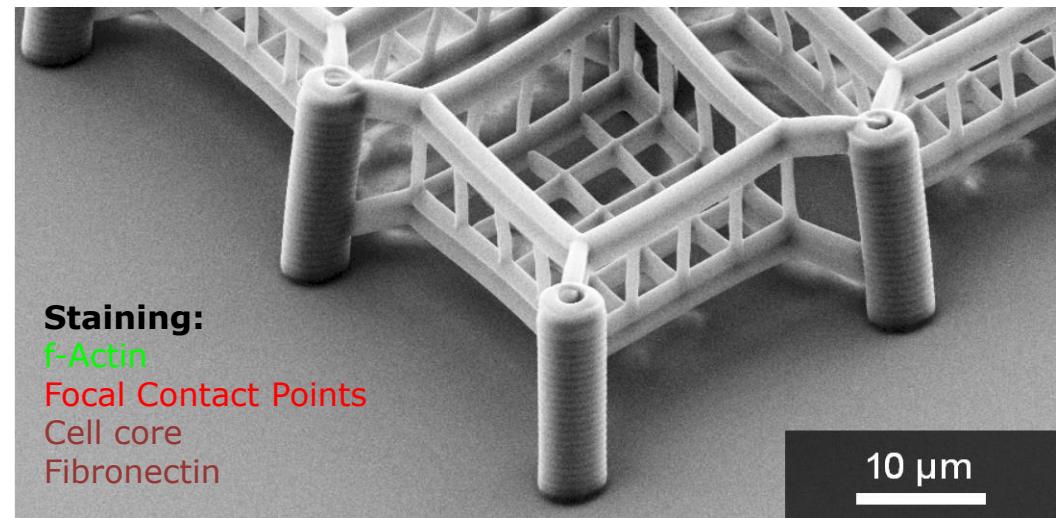
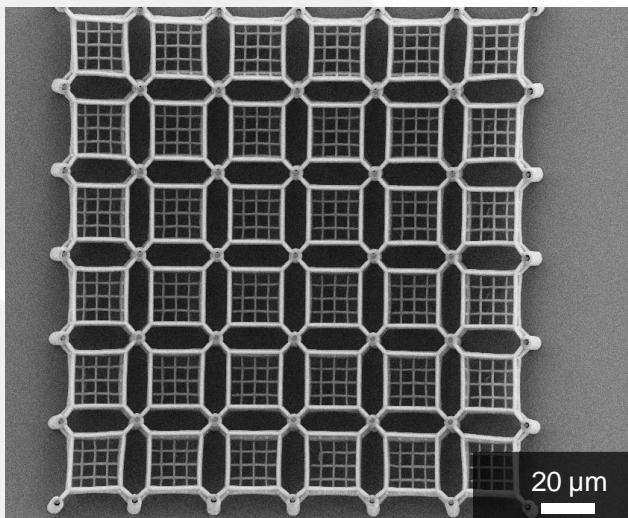


Rapid Prototyping



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Scaffolds for Cells



ORMOCERE, J. Fischer, F. Klein, T. Striebel, M. Bastmeyer, Karlsruher Institut für Technology (KIT)

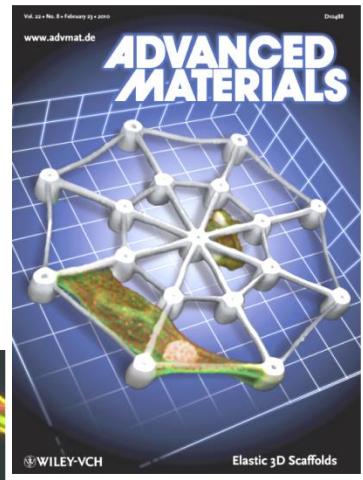
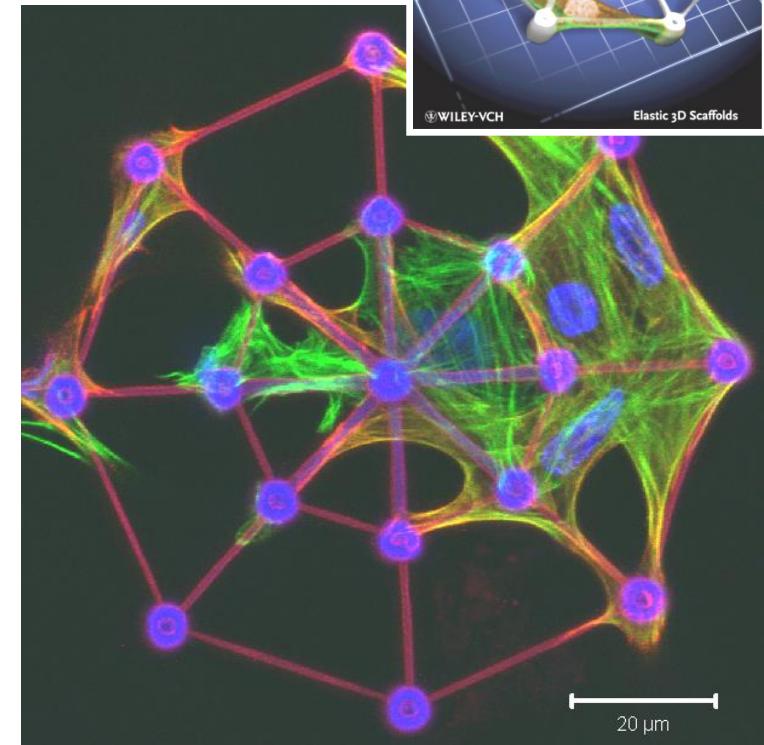
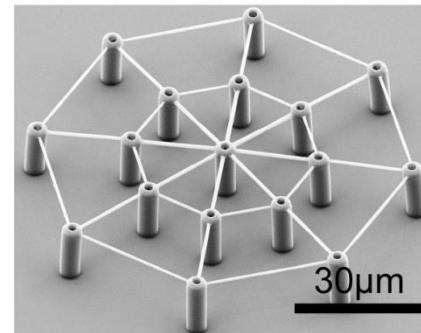
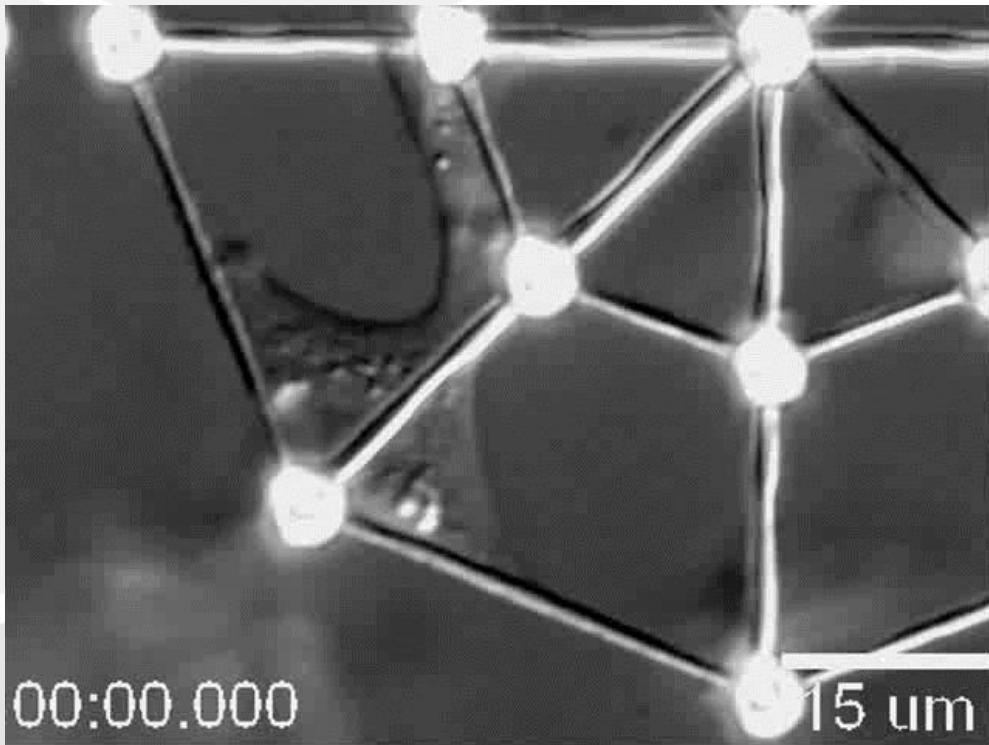


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A Gym for Cells

- Primary culture of chicken heart cells

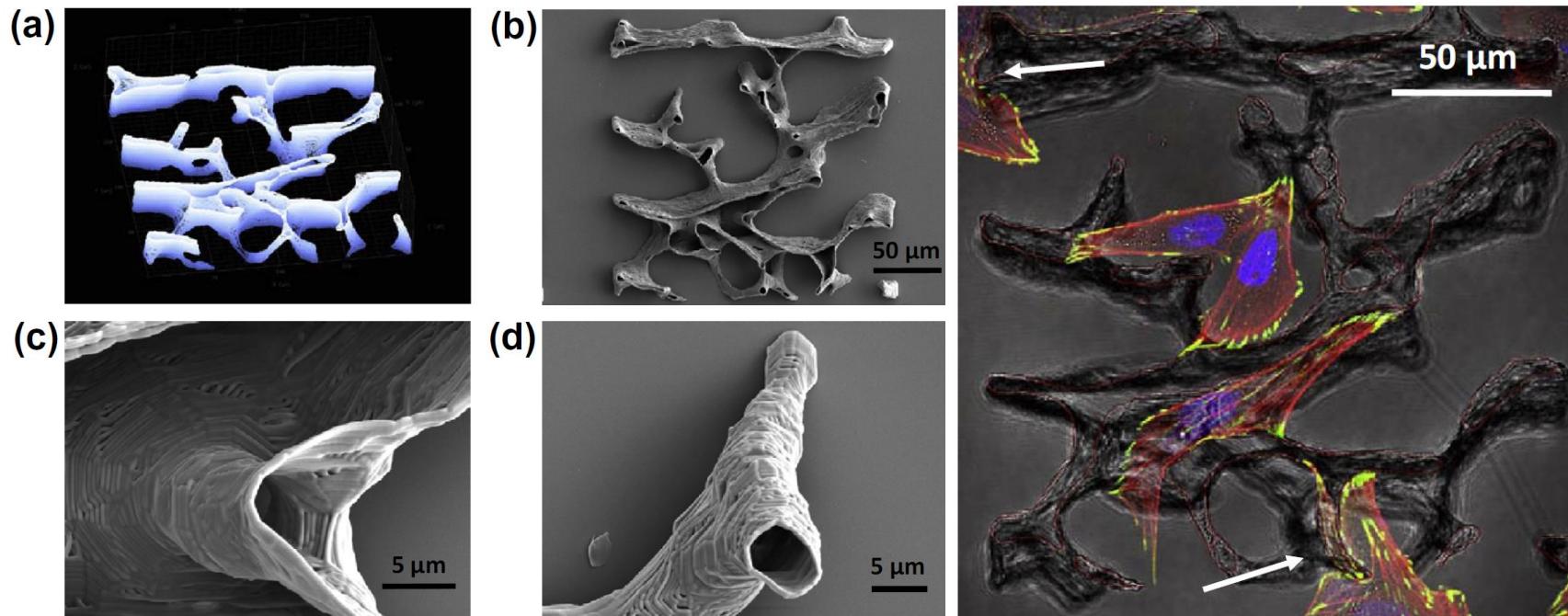
F. Klein *et al.*, Adv. Mater. **22**, 868 (2010)





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The Osteoprint



A. Marino et al., Acta Biomaterialia Vol.10 Issue 10, (2014) 4304-4313

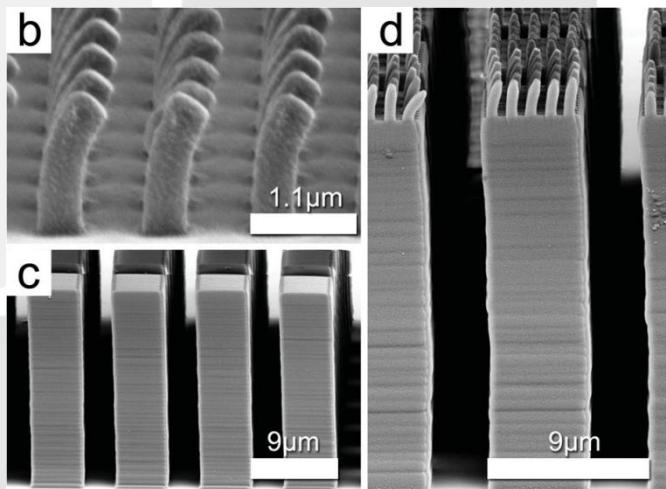
- Artificial trabecula-like structure
- For bone-like cell differentiation

Salvinia effect:

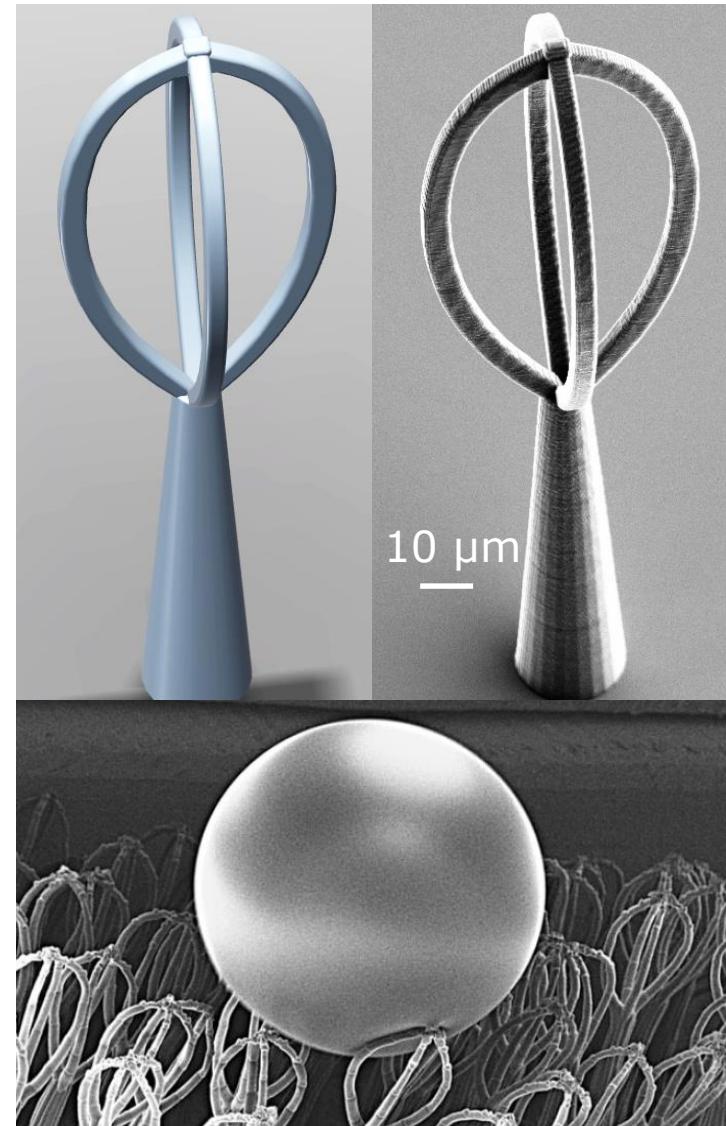
- Floating fern
- Air retention prevents getting moldy when drowned under water
- Application: Friction reduction of ships

Gecko effect:

- Application: Adhesion based on hierarchical structure



M. Röhrig et al., Small 19, 2918 (2012)

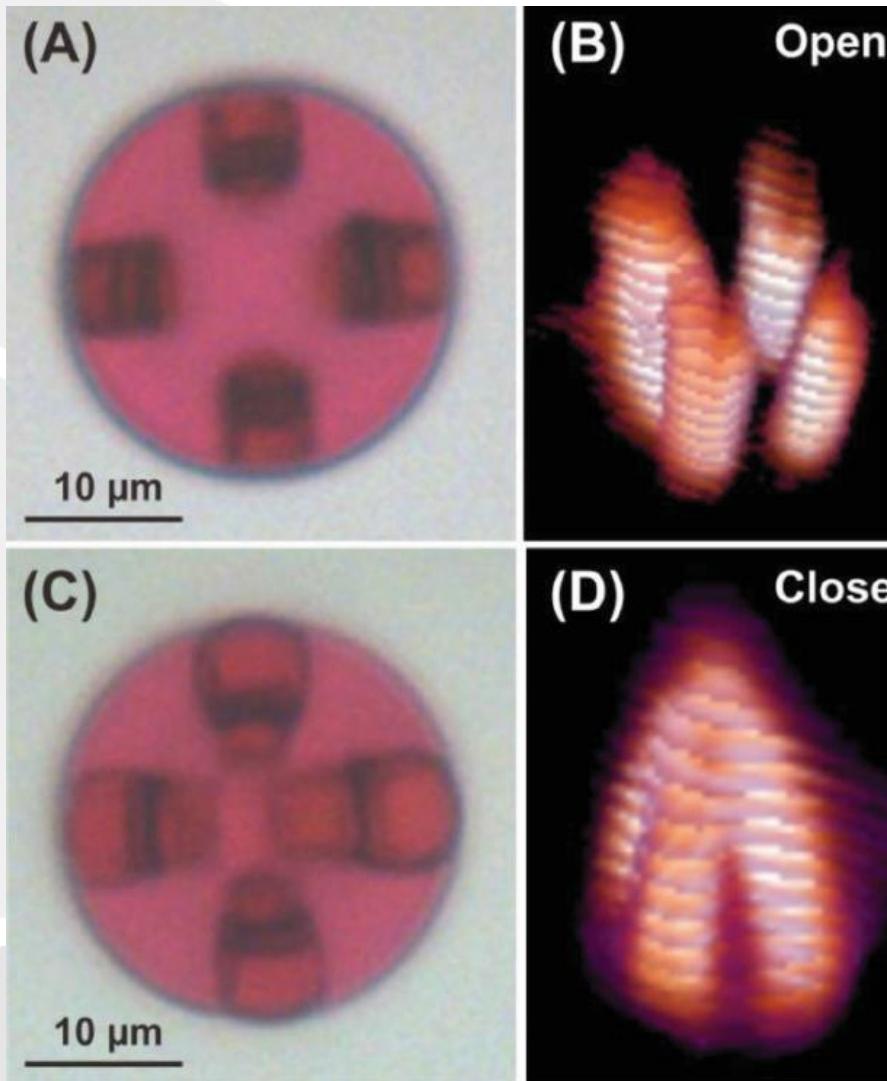


W. Barthlott, et al. Adv. Mater. 22, 2325 (2010)



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Protein hydrogels

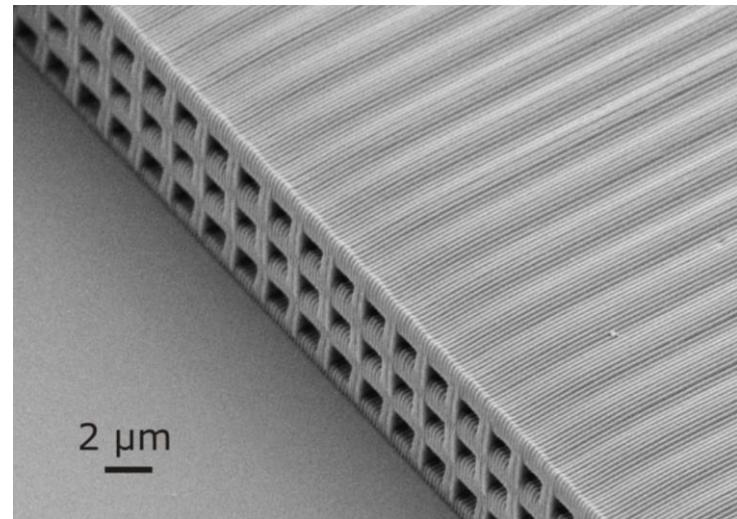
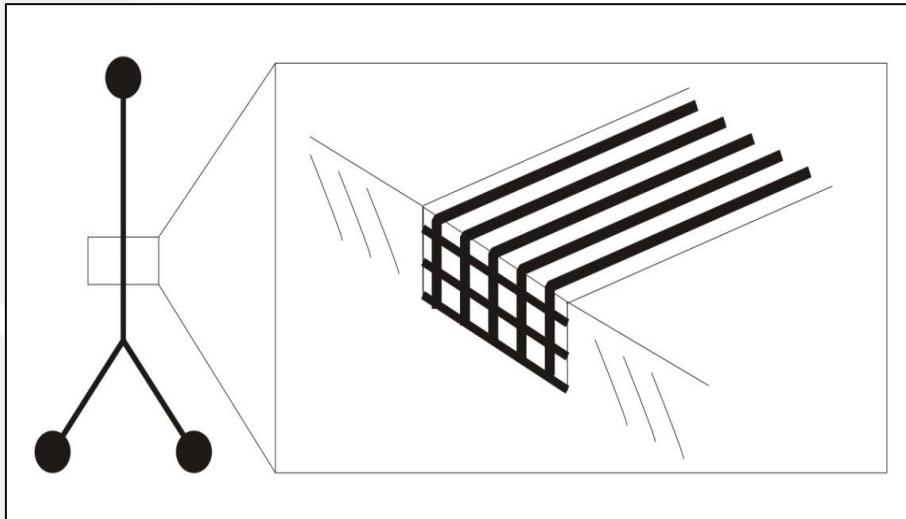


Direct fabrication
of chemically
responsive
microactuators.

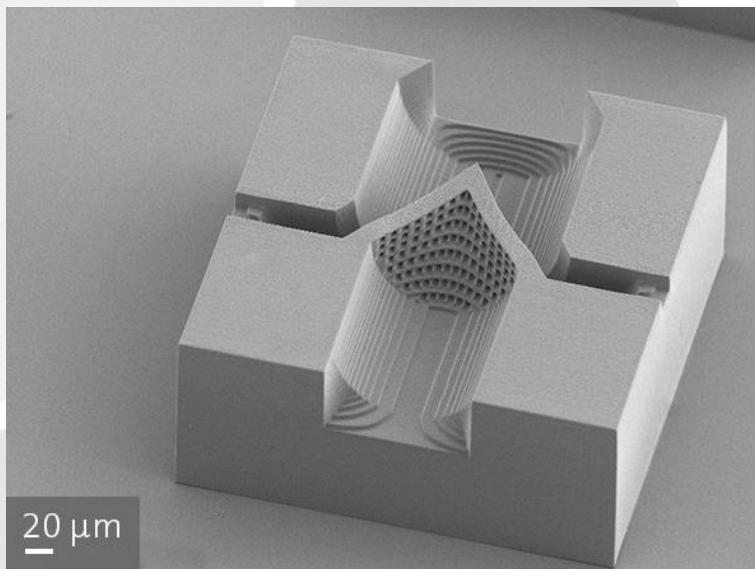


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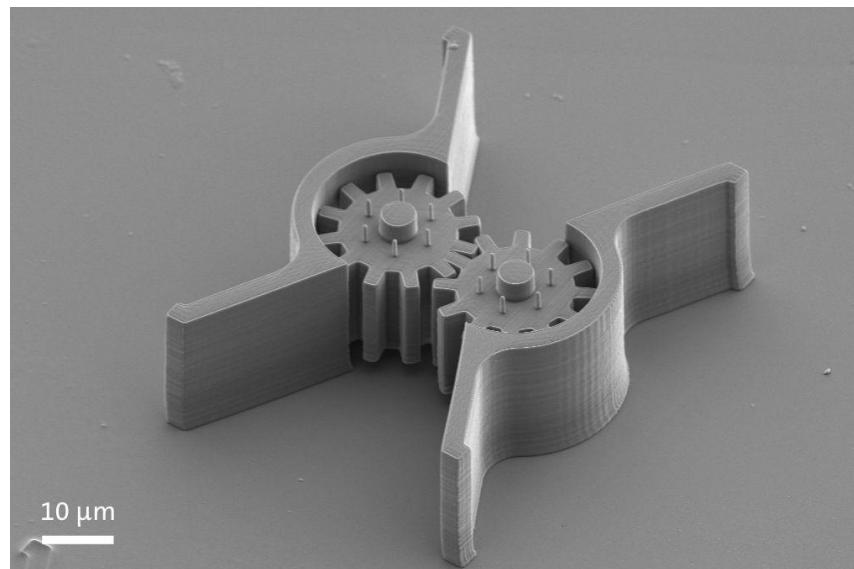
Writing of Microfluidic Elements



Design by A.-M. Haghiri-Gosnet, LPN-CNRS, France



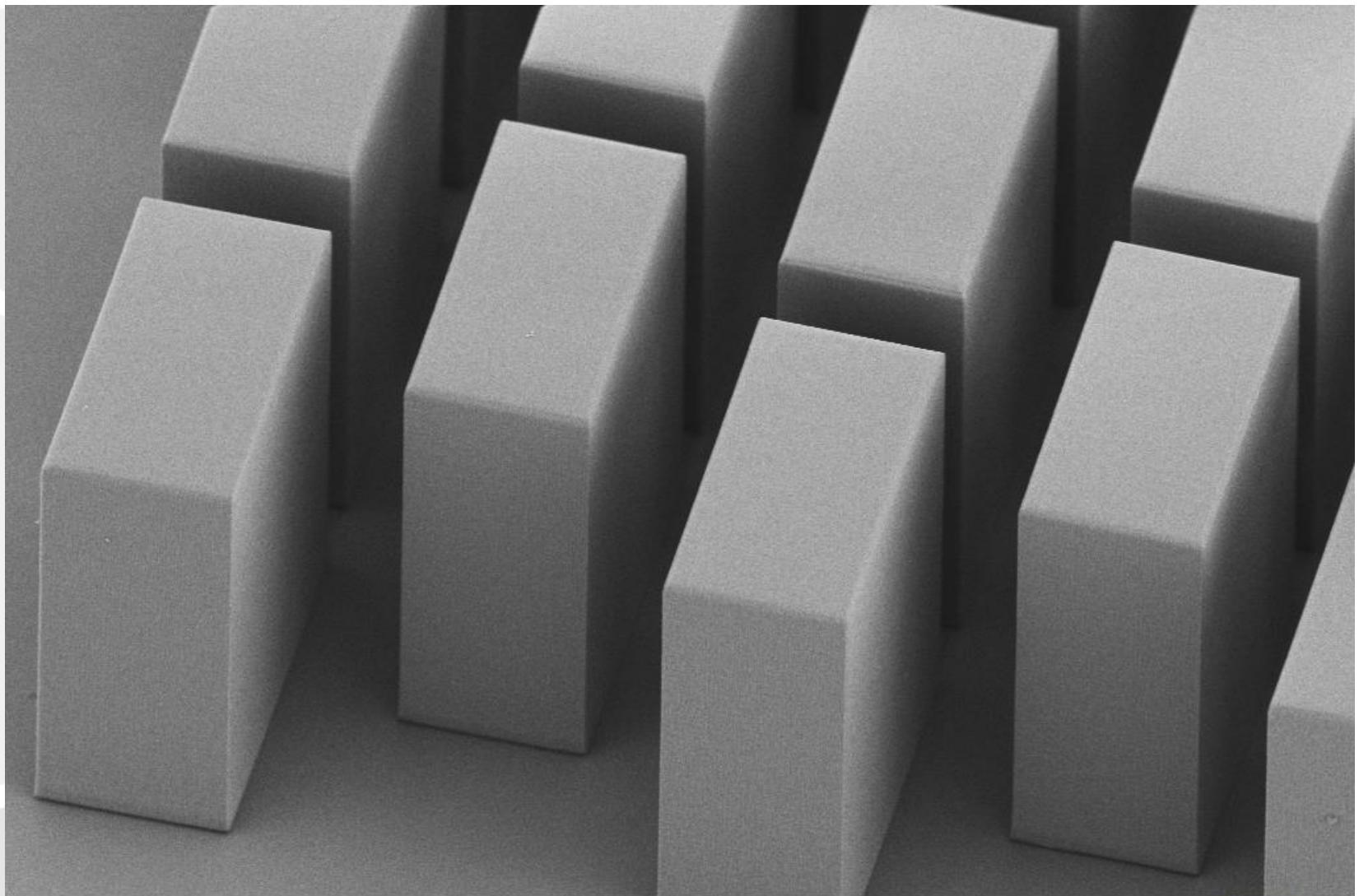
Microfluidic filter element structured in SU-8
(design provided by IMSAS)





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Capillary Micropump



10 μm

Stage at T = 0.0 °
Mag = 1.00 K X

EHT = 5.00 kV
WD = 6.6 mm

Signal A = SE2
File Name = SN464_778_06.tif

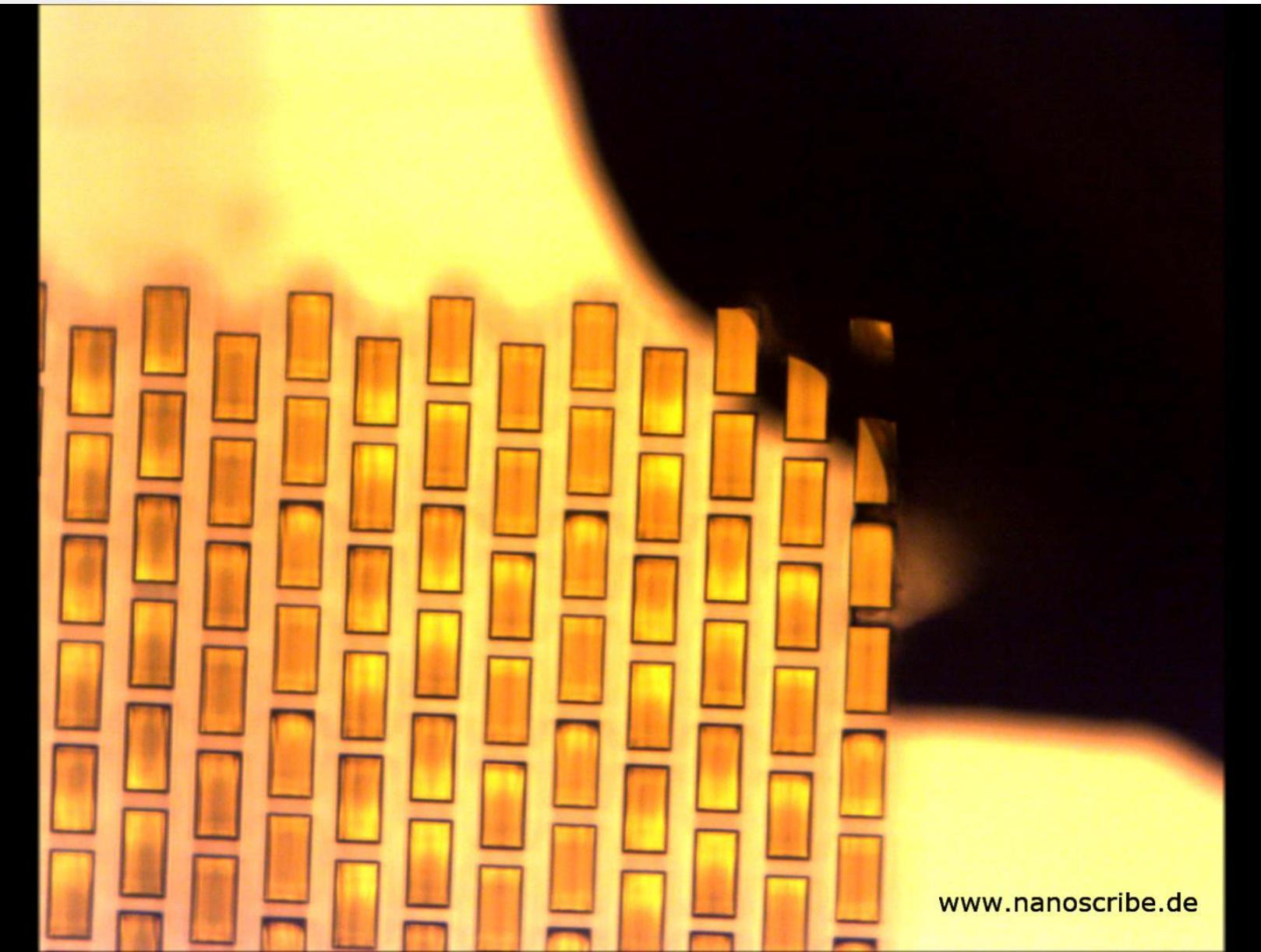
Date :18 Jun 2013
Time :16:27:19





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Capillary Micropump

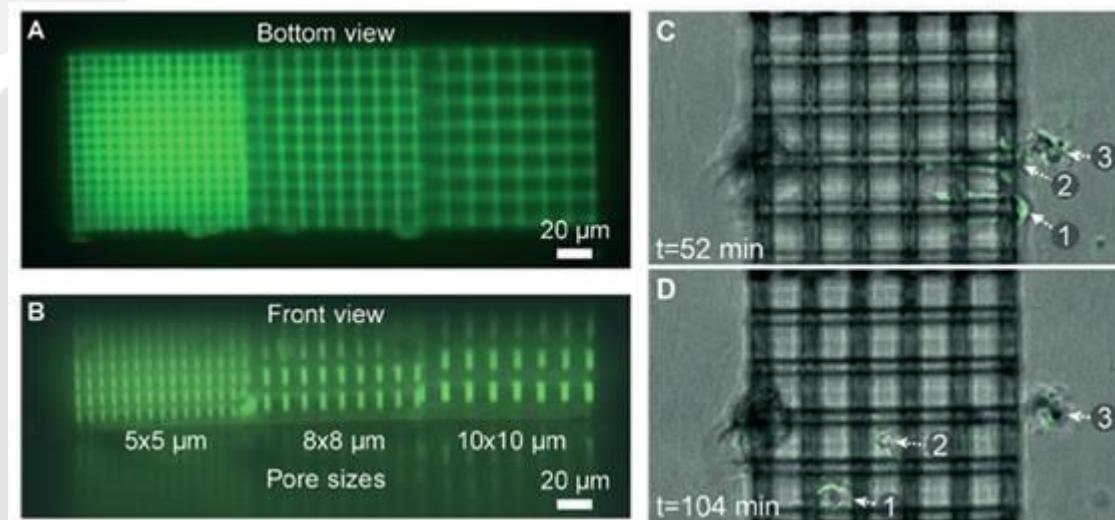


www.nanoscribe.de



In-chip 3D networks for cell studies

- In-chip fabrication inside of commercial microfluidic chip
- 3D networks with different pore sizes
- Dendritic cell motility studies through the confined spaces of the 3D structure (cells labelled as 1,2,3):



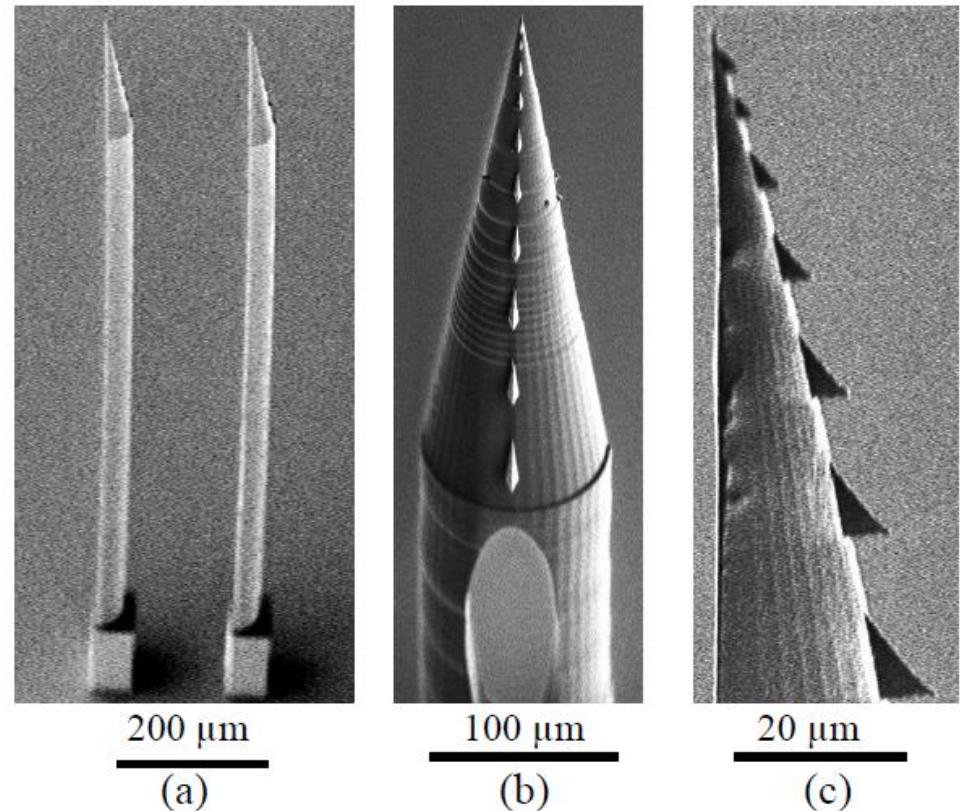
- M.H.Olsen et al. In-chip fabrication of free-form 3D constructs for directed cell migration analysis, Lab Chip, 2013, 13, 4800-4809, [DOI: 10.1039/c3k50930c](https://doi.org/10.1039/c3k50930c)



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Bio-mimicking painless microneedles

- Immitates mosquito's proboscis
- 2 mm height
- Conically sharpened tip
- Medical applications: drug delivery and blood collection
- Hollow microneedle sucks blood by capillary force



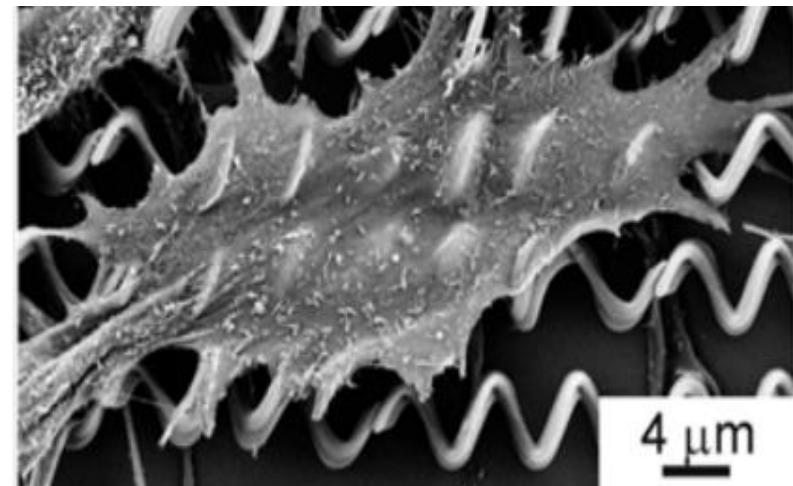
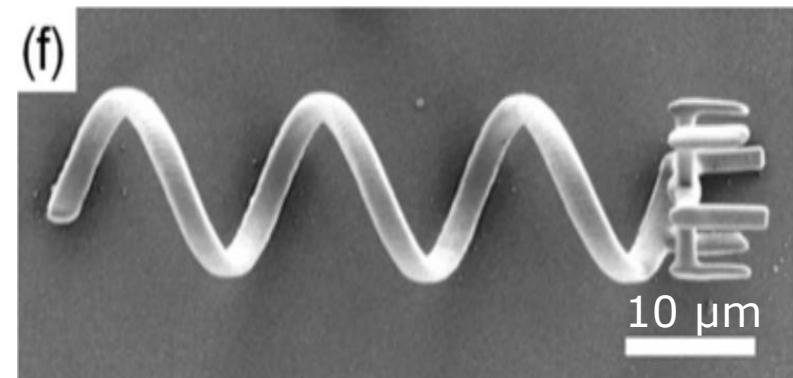
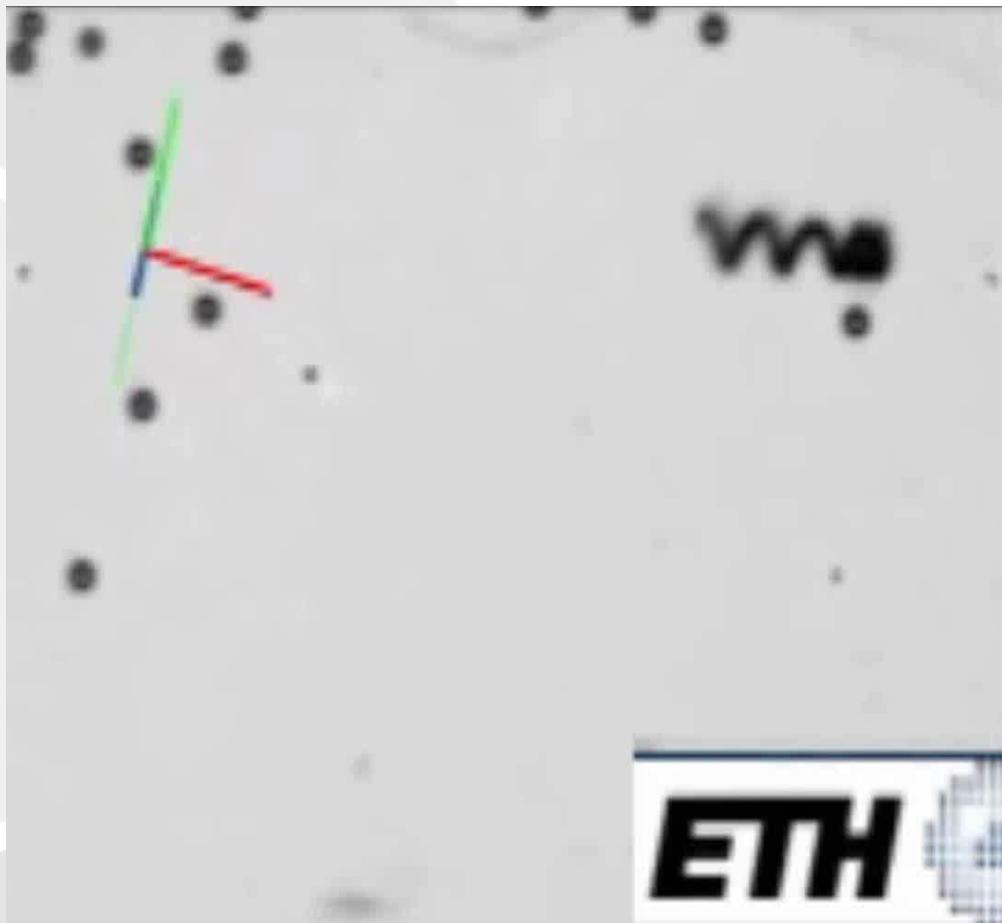
Fabrication of microneedles precisely imitating mosquito's proboscis by nanoscale three dimensional laser lithography and its characterization

Suzuki, M., Sawa, T., Terada, Y., Takahashi, T., Aoyagi, S.
Solid-State Sensors, Actuators and Microsystems (TRANSDUCERS), 2015,
DOI: 10.1109/TRANSDUCERS.2015.7180876



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Magnetic Helical Micromachines

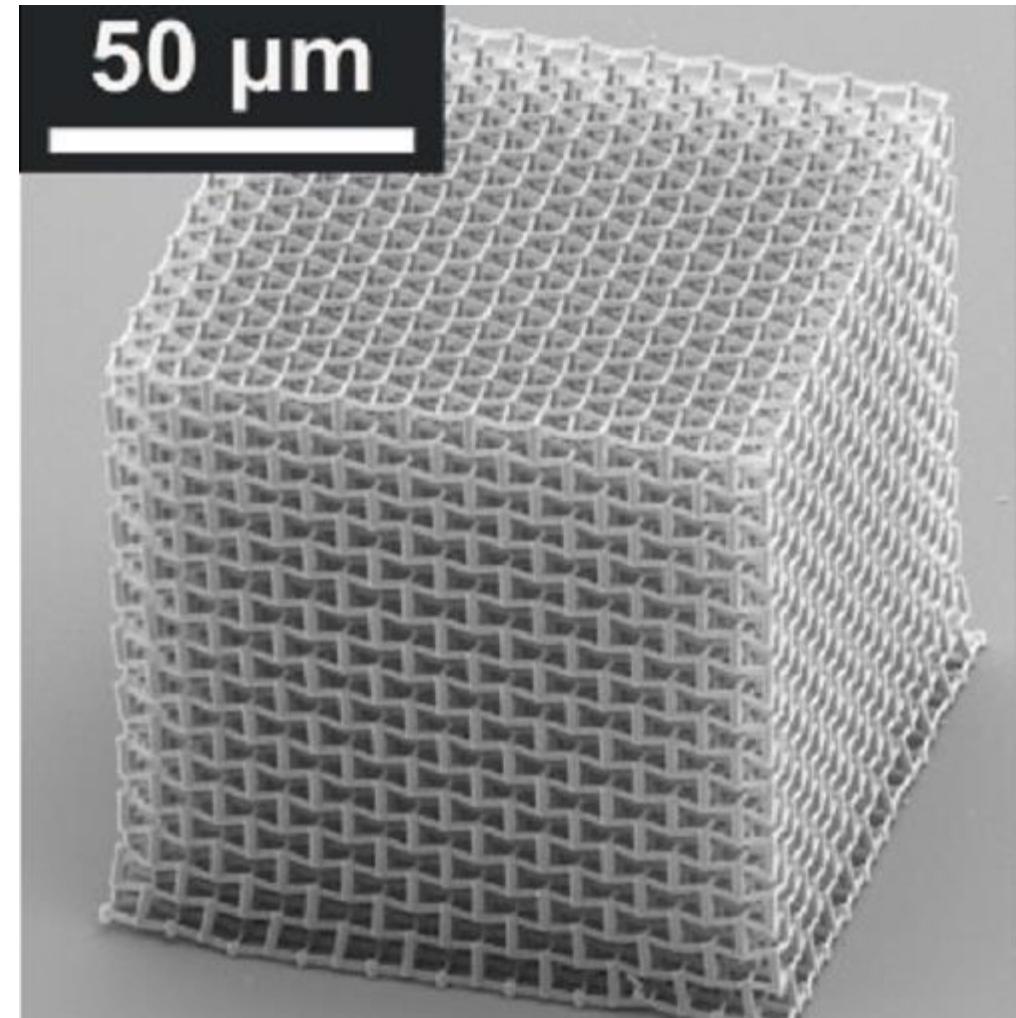
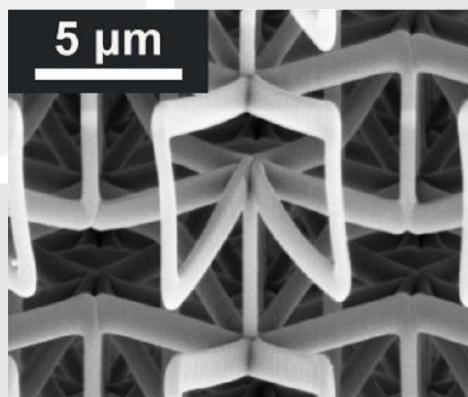
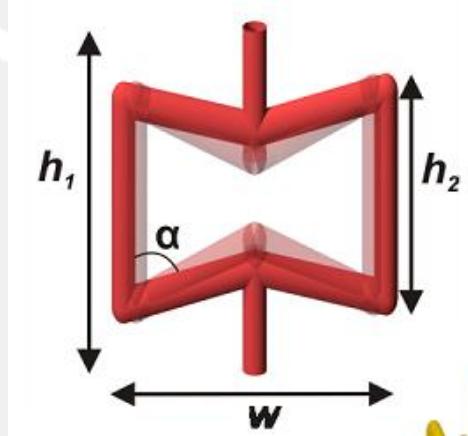




Mechanical Metamaterials

Auxetics:

- Tunable Poisson's ratio ν
- $-0.12 < \nu < +0.13$



T. Bueckmann et al., Advanced Materials 24, 2710 (2012)

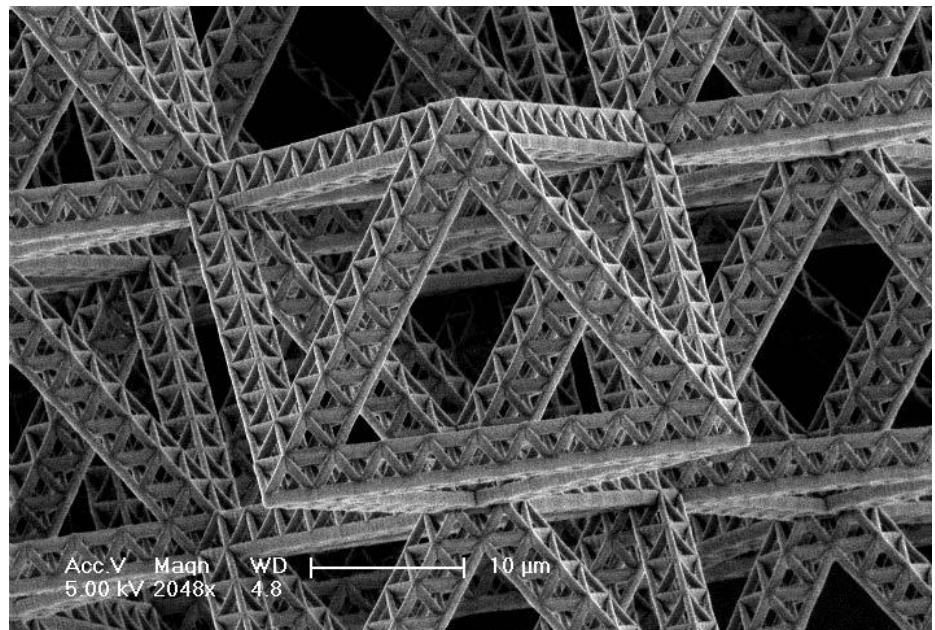
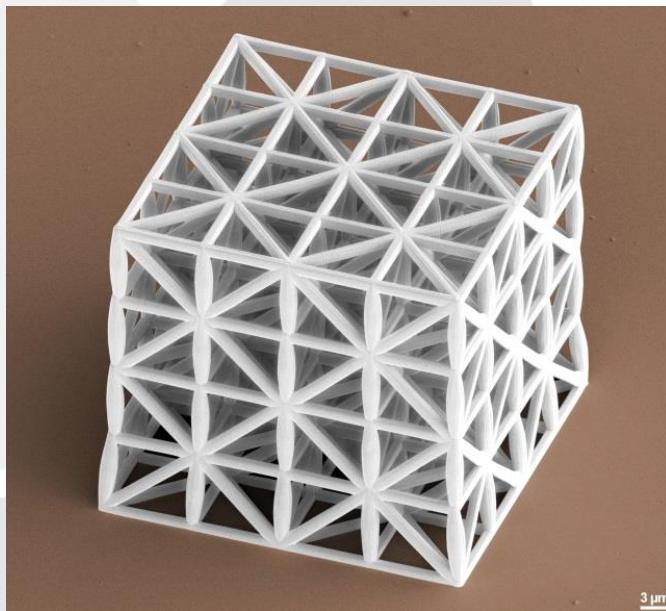


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Ultralight Microlattices

Applications:

- Thermal insulation
- Battery electrodes
- Acoustic/vibration/shock damping



J. R. Greer et al., Science 345, 1322 (2014)
<http://www.caltech.edu/content/miniature-truss-work>

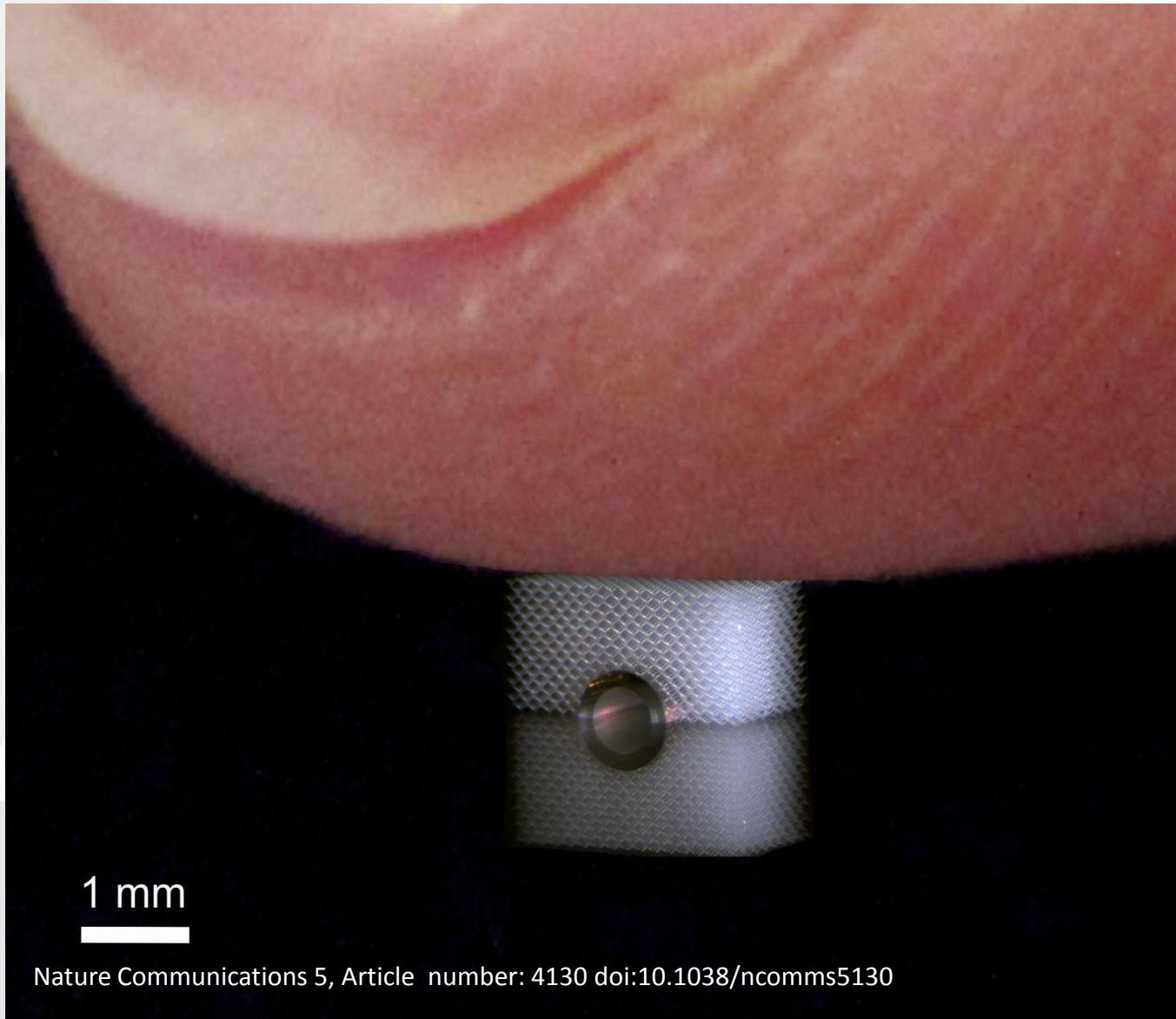
Ultra-lightweight designer mechanical material

J. Bauer et al., PNAS, doi: 10.1073/pnas.1315147111 (2014)



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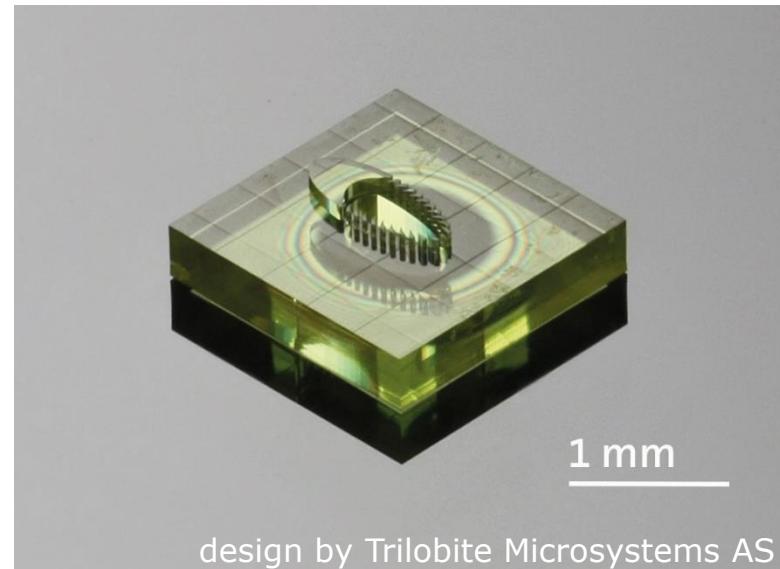
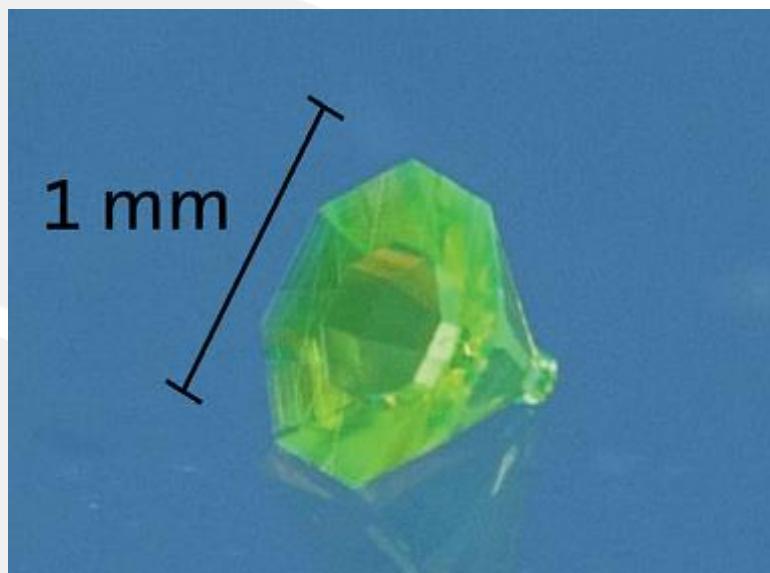
Unfeelability cloak





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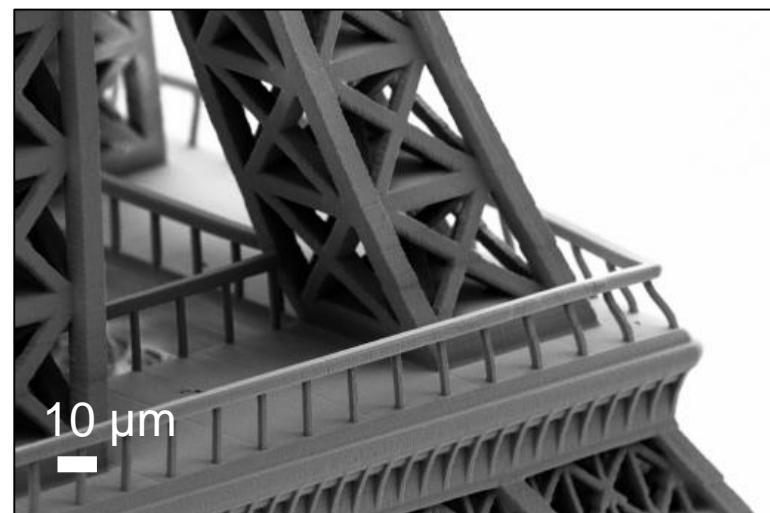
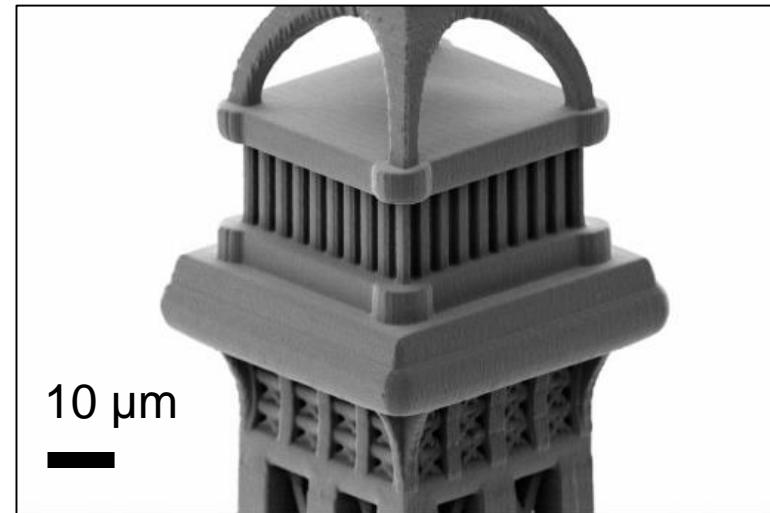
Meso-scale objects





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3D Micro-Printing





nanscribe

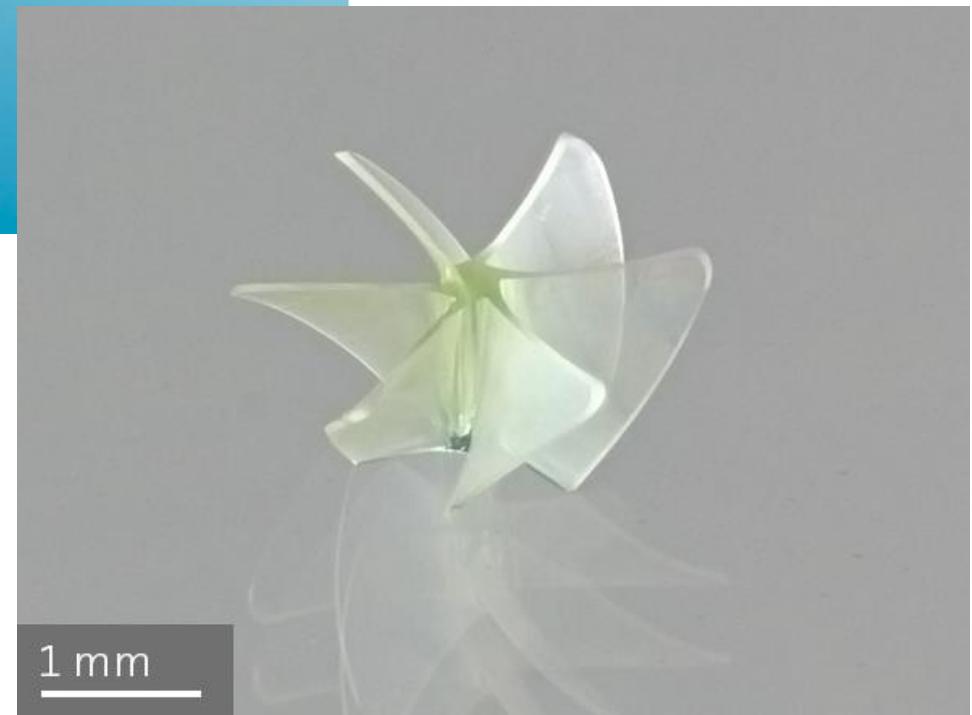
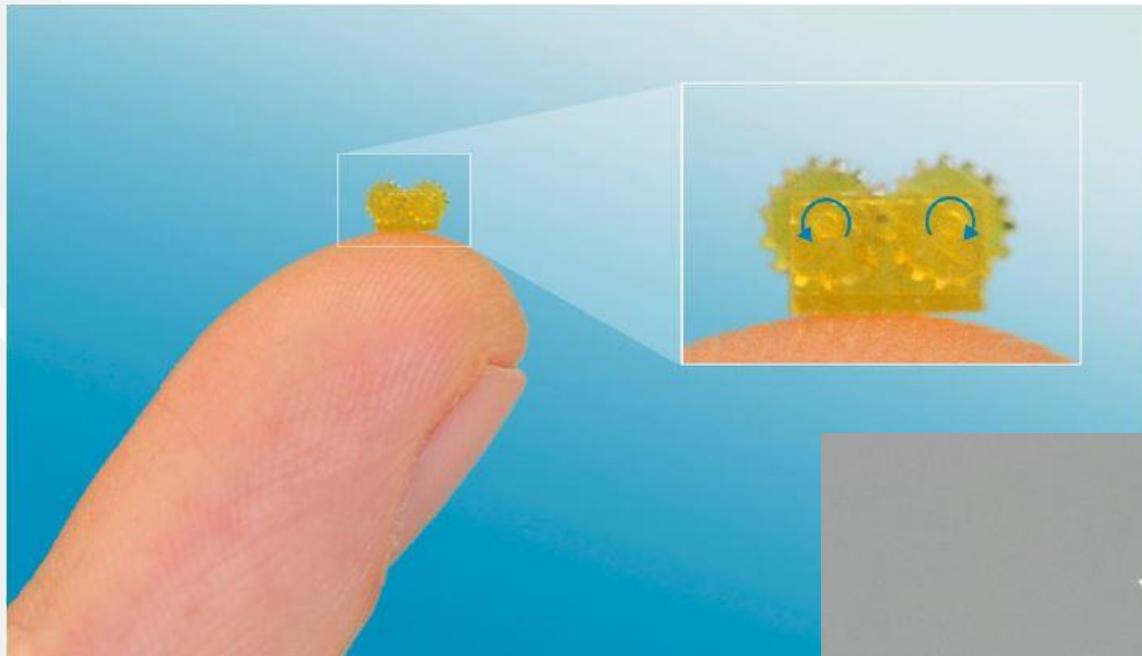
3D Micro-Printing





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μ -3D Printing in mm





Castle of Karlsruhe for its 300th anniversary

Thank you for your attention



10 mm

Castle of Karlsruhe for its 300th anniversary